

Optimization of Photodetection Analysis for MXene Thin Films

Kristine Loh

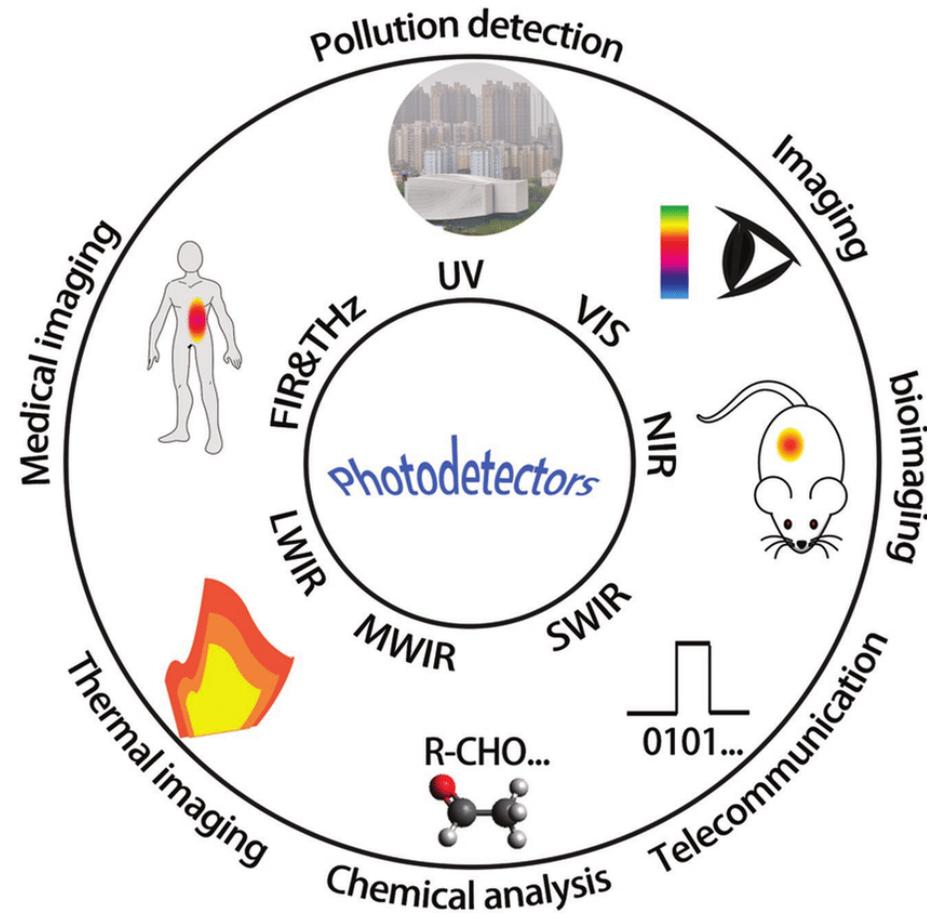
MS Thesis Defense

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Thesis Advisor: Prof. Jason Baxter

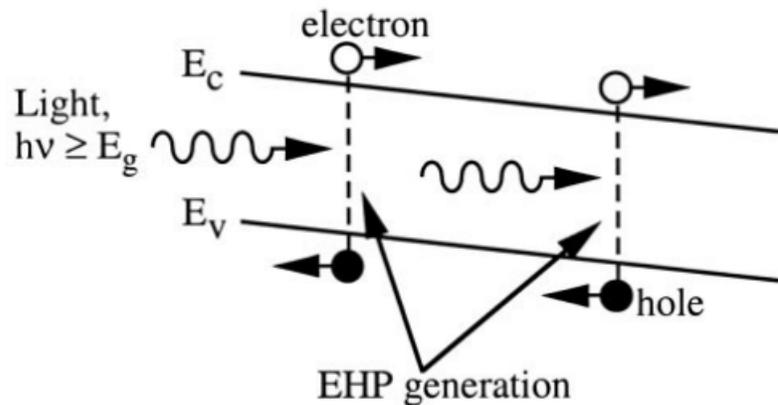
Committee Members: Prof. Yury Gogotsi | Prof. Steven May

Photodetectors

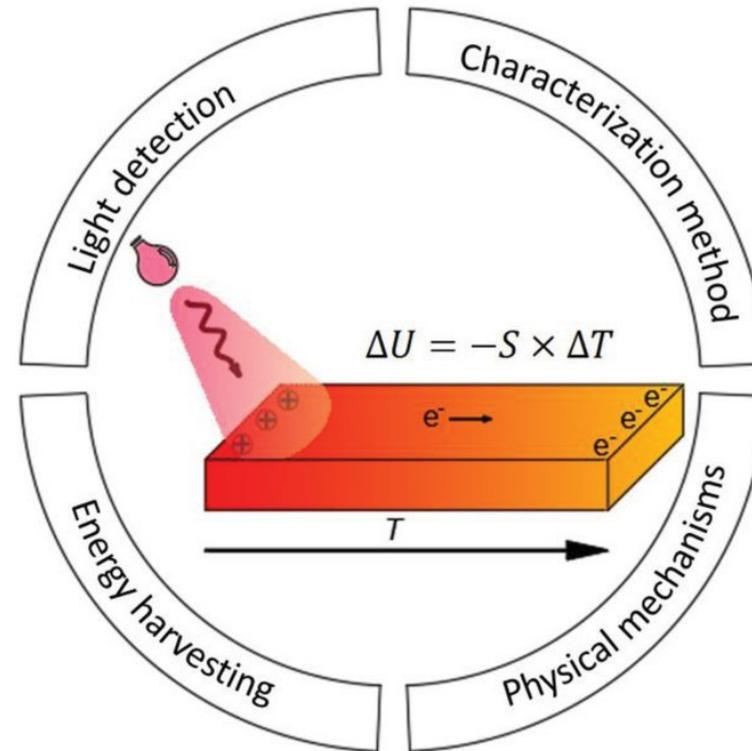


Mechanisms for Photodetection

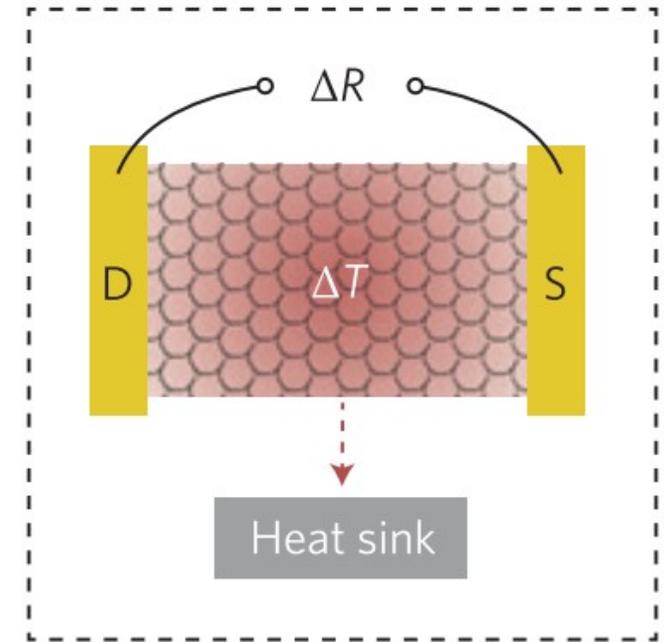
Photovoltaic Effect or Photoconductive Effect



Photothermoelectric Effect

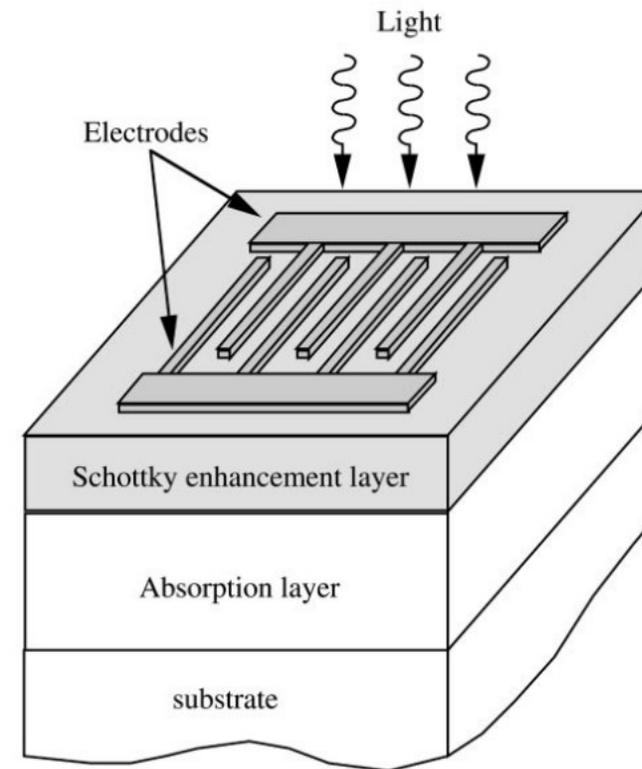


Bolometric Effect



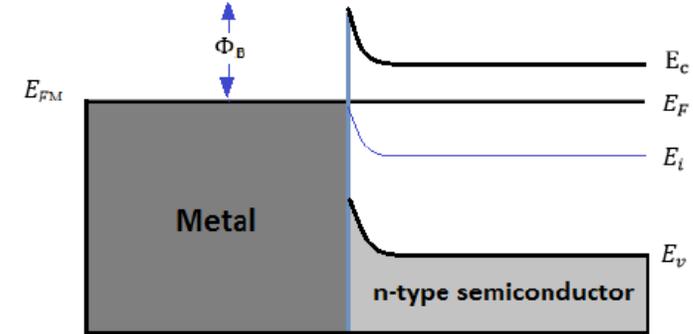
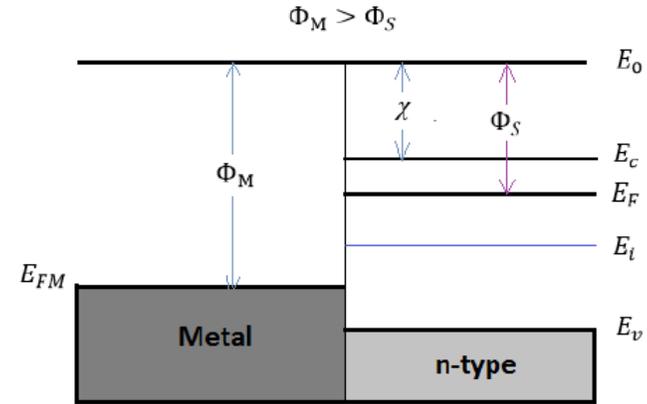
Photodetector Structures

- Absorption layer
 - Typically made of semiconducting materials
 - Three main spectrum zones: ultraviolet (10 – 400 nm), visible (400 – 760 nm), and infrared (760 nm – 2.5 μm)
- Electrical contacts (electrodes)
 - Typically made of metallic materials
 - Can be transparent depending on the structure

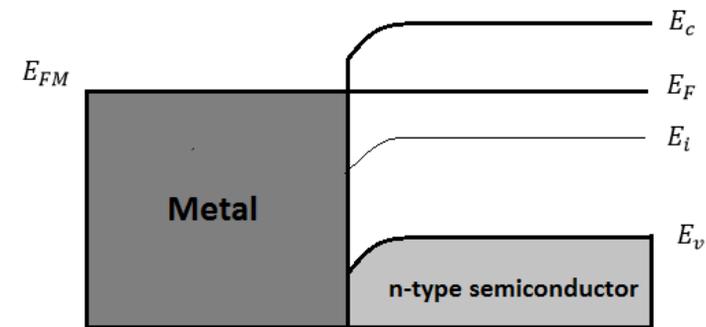
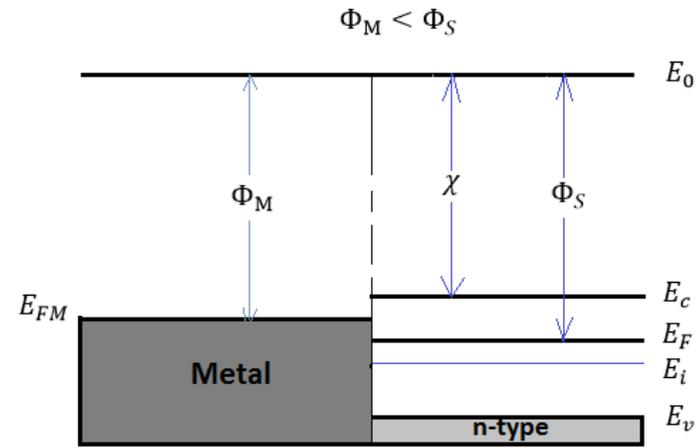


Contacts

Schottky (Rectifying) Contact

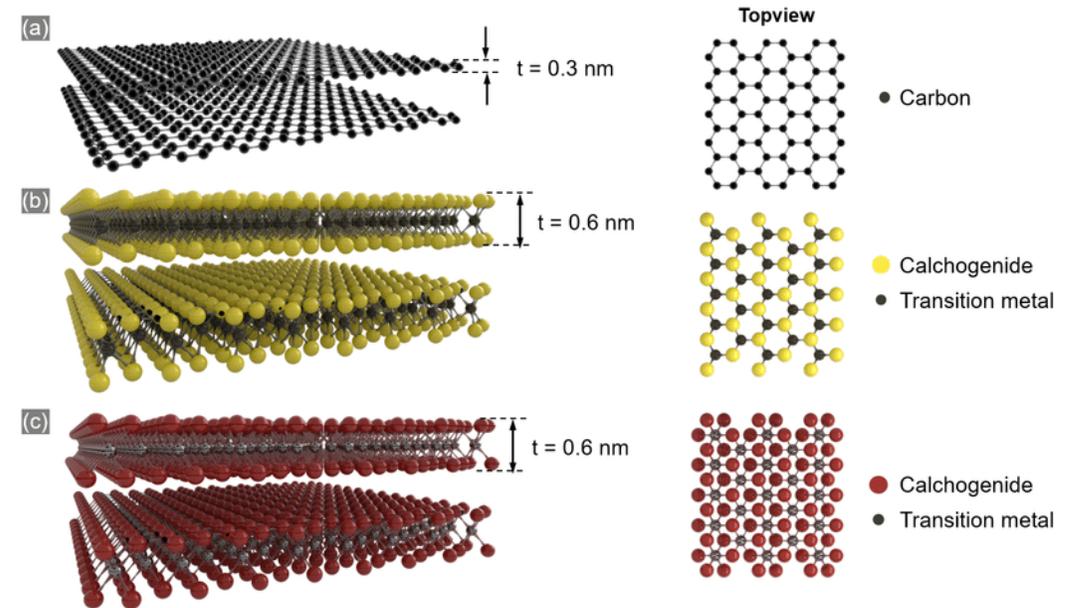


Ohmic Contact



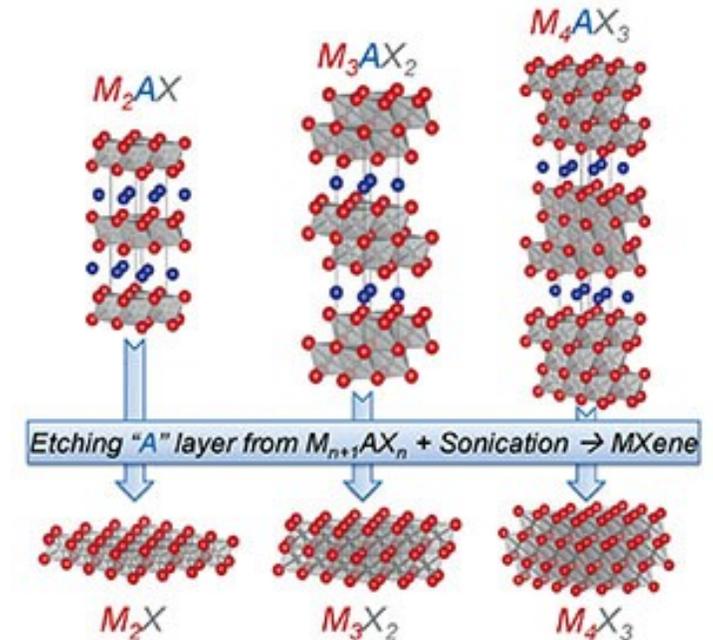
2D Materials for Photodetection

- Ease of processing and desirable optoelectronic properties
- Mechanical strength
- Thickness tunable band gap
- Examples:
 - Graphene
 - Transition metal dichalcogenides (TMDs) - MoS_2



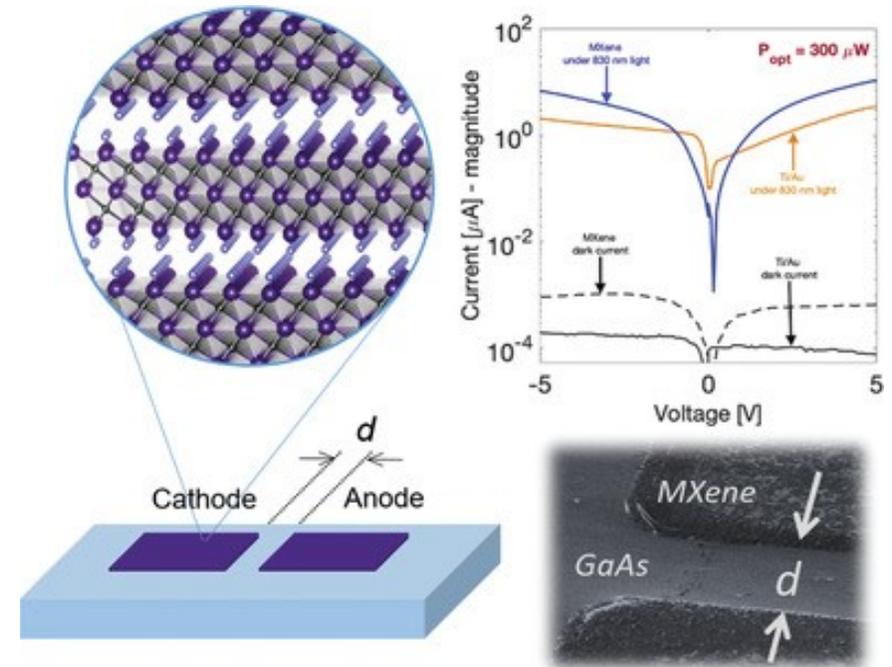
Introduction to MXenes

- Discovered at Drexel University in 2011
- Novel class of 2D materials
- General formula of $M_{n+1}X_nT_x$
 - M: early transition metal
 - X: either carbon or nitrogen
 - T: functional group
 - n is between 1 to 4
- Tunable properties based on a variety of surface terminations and chemical compositions



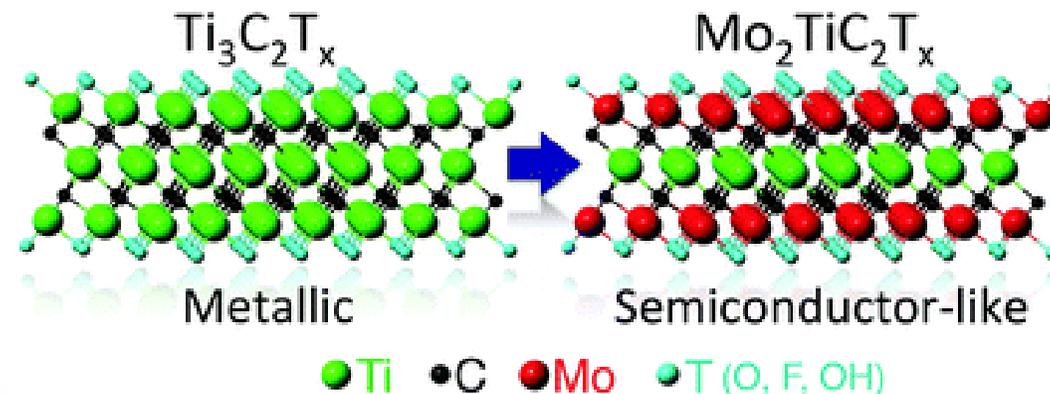
Why MXenes?

- High electronic conductivity
- Hydrophilic surface
- Low cost
- Facile synthesis methods
- Tunable properties
 - Work function
 - Band structure



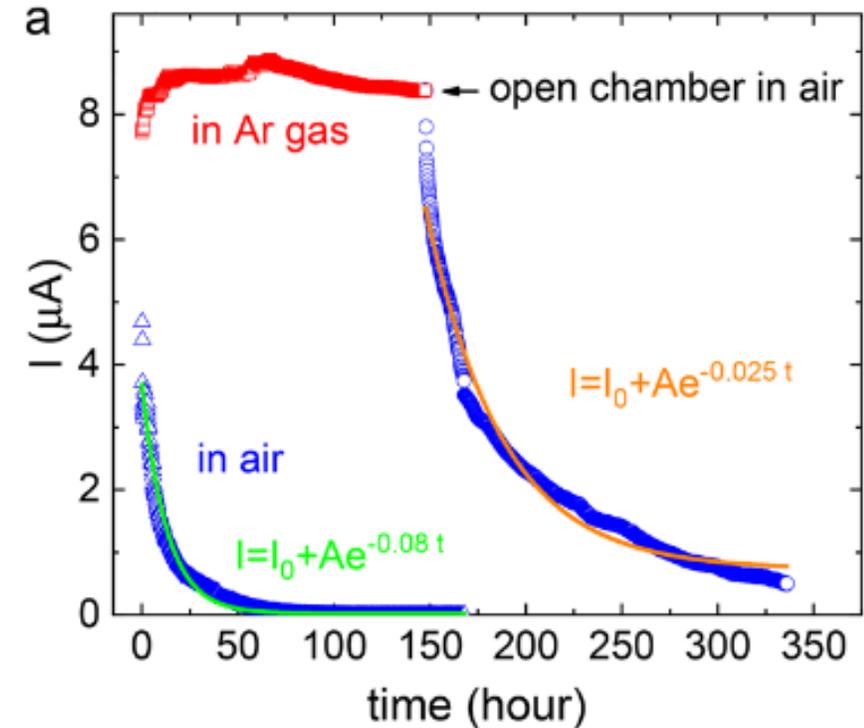
Why $\text{Ti}_3\text{C}_2\text{T}_x$ and $\text{Mo}_2\text{TiC}_2\text{T}_x$?

- $\text{Ti}_3\text{C}_2\text{T}_x$ is heavily studied, but $\text{Mo}_2\text{TiC}_2\text{T}_x$ is not
- Will the same testing method apply to both materials?
- $\text{Mo}_2\text{TiC}_2\text{T}_x$ is semiconductor-like, can this be verified using this test method?



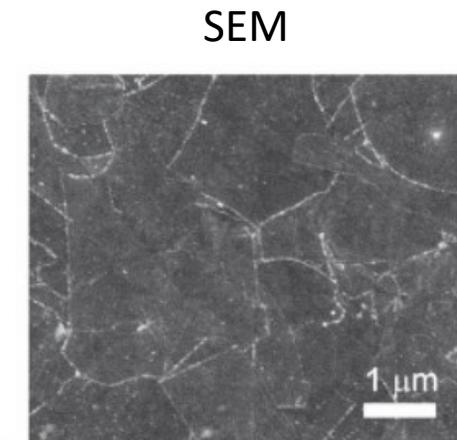
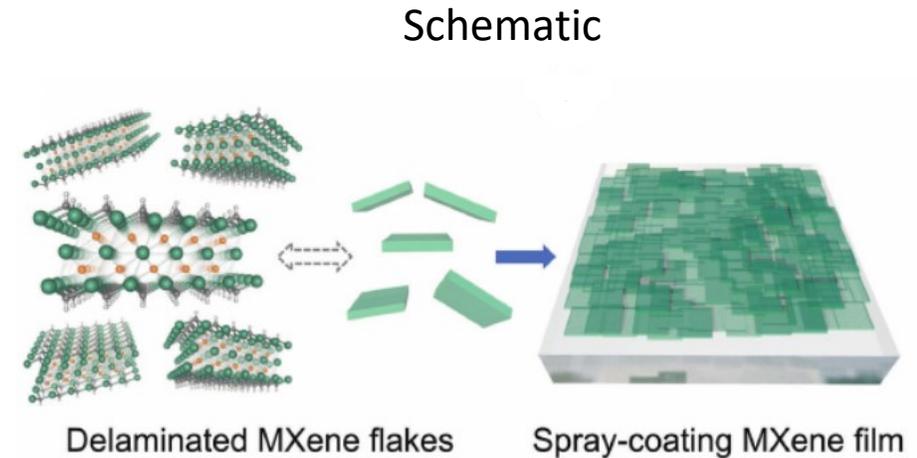
Photoresponse Influences

- Environment
- Ohmic vs. Schottky contacts
- Resistive-capacitive effects
- Electronic interactions
- Heating



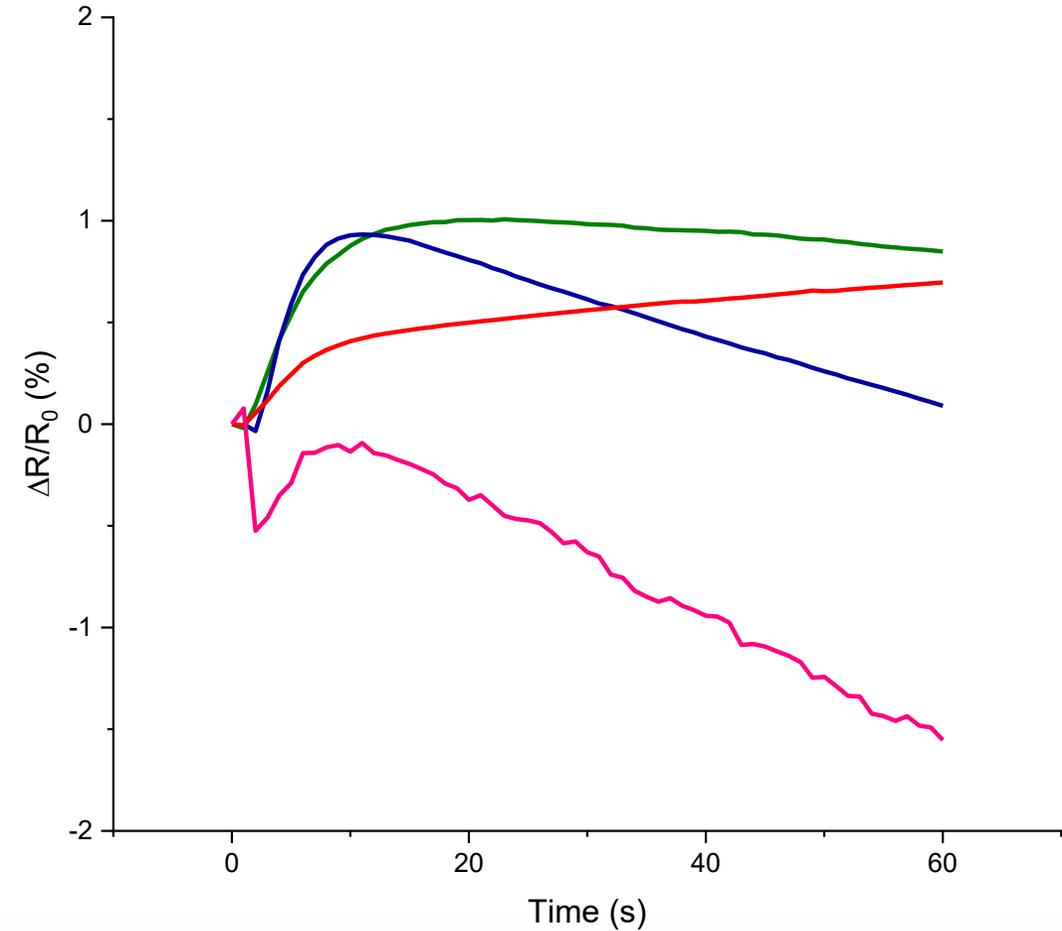
Interflake Interactions for 2D Materials

- Strong in-plane electronic interactions
- Weak out-of-plane van der Waals interactions
- Intercalants: molecules situated between two layers
 - Increase spacing between layers
 - Contribute to electronic properties



Photoresponse Characteristics

- Sign
- Shape
- Speed
- Strength

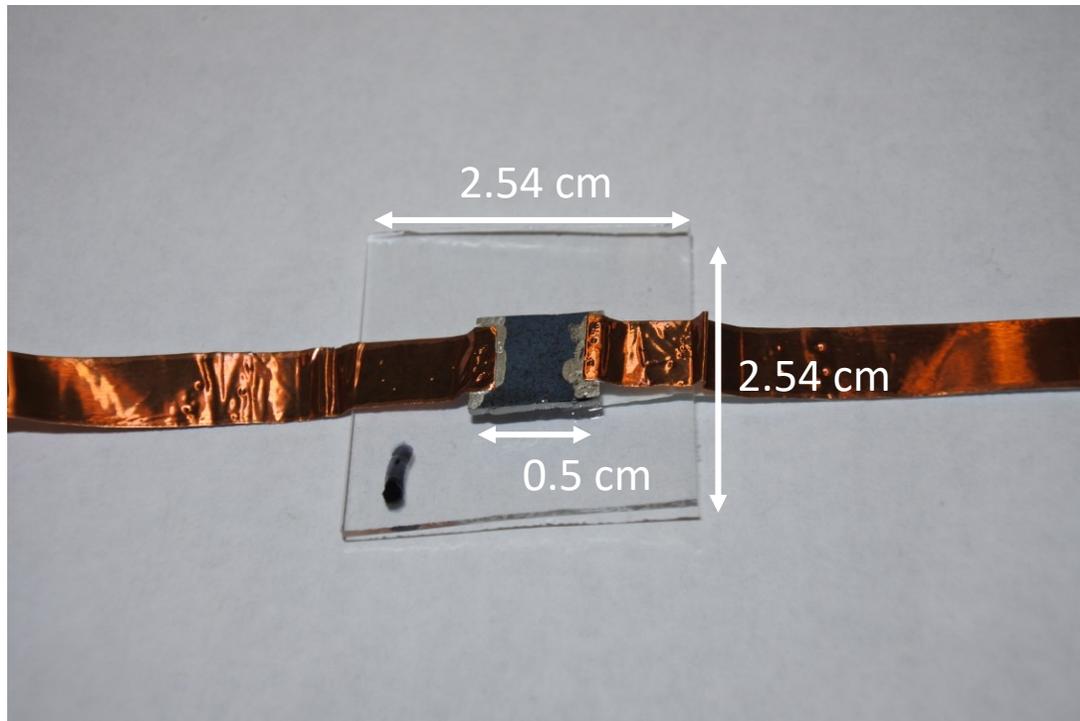


Objectives

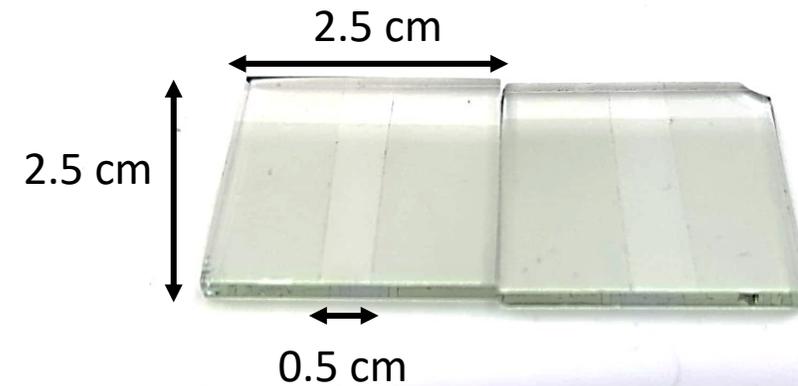
1. Determine best practices for optoelectronic characterization of MXenes
2. Probe effect of external stimuli on photoresponse of MXenes
3. Understand fundamental mechanisms of MXene optoelectronic behavior

Substrate Types

Pristine Glass Slide

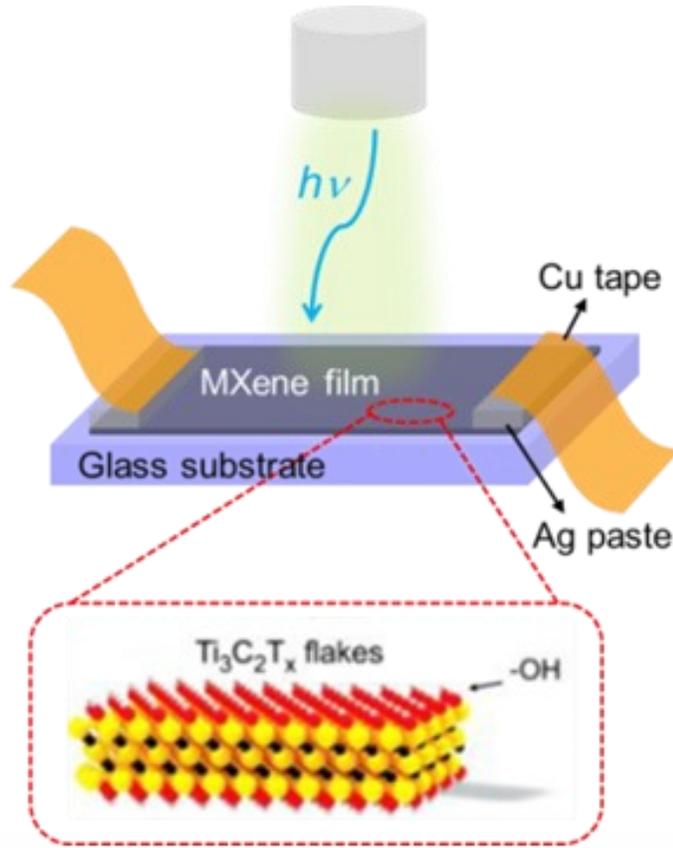


Patterned FTO

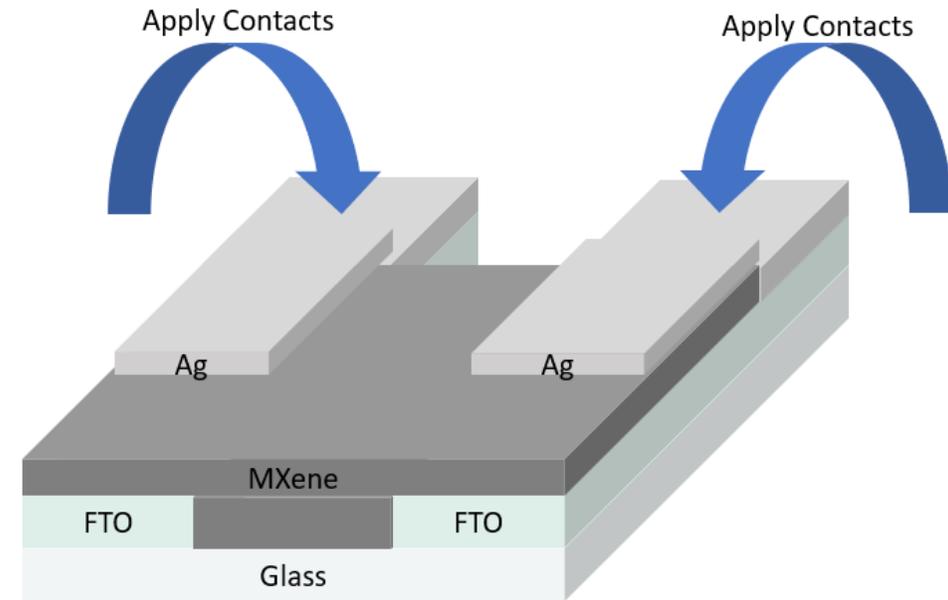


Contact Method

Ag Paint – Cu Tape

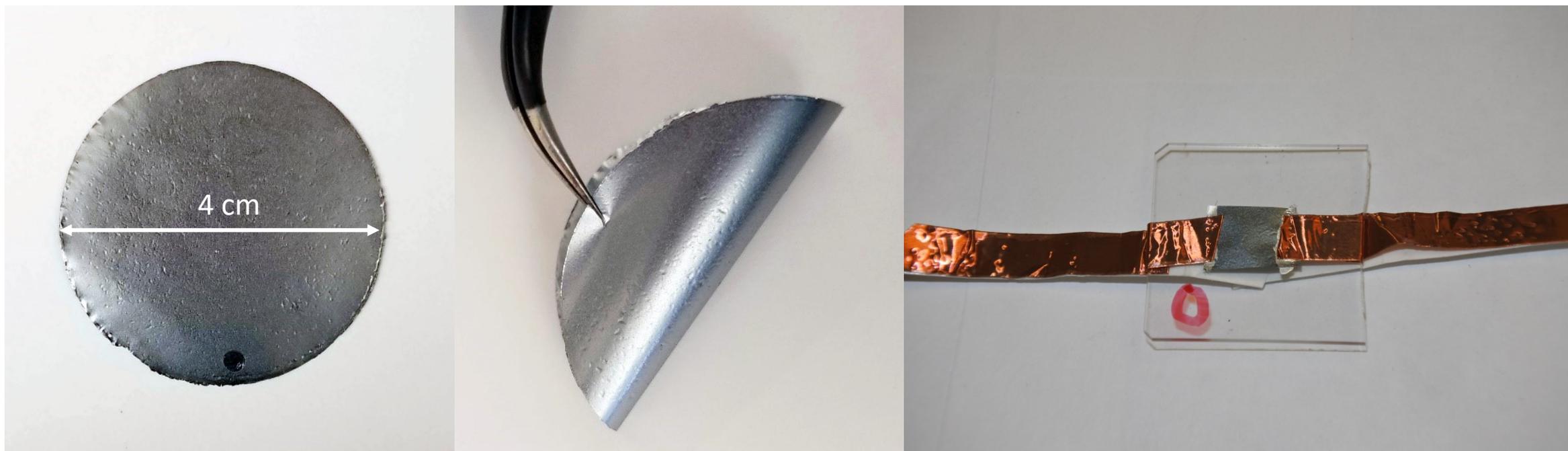


FTO or Ag Paint – FTO

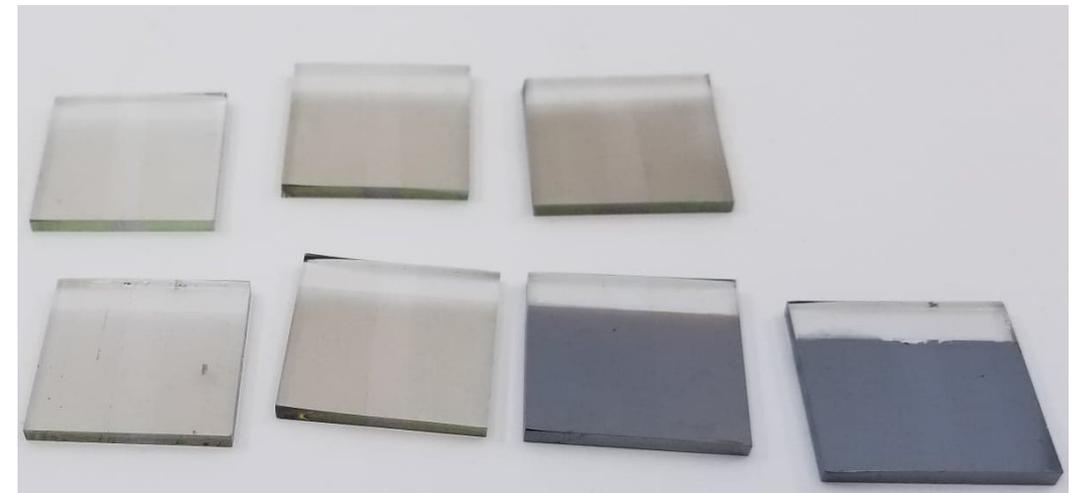
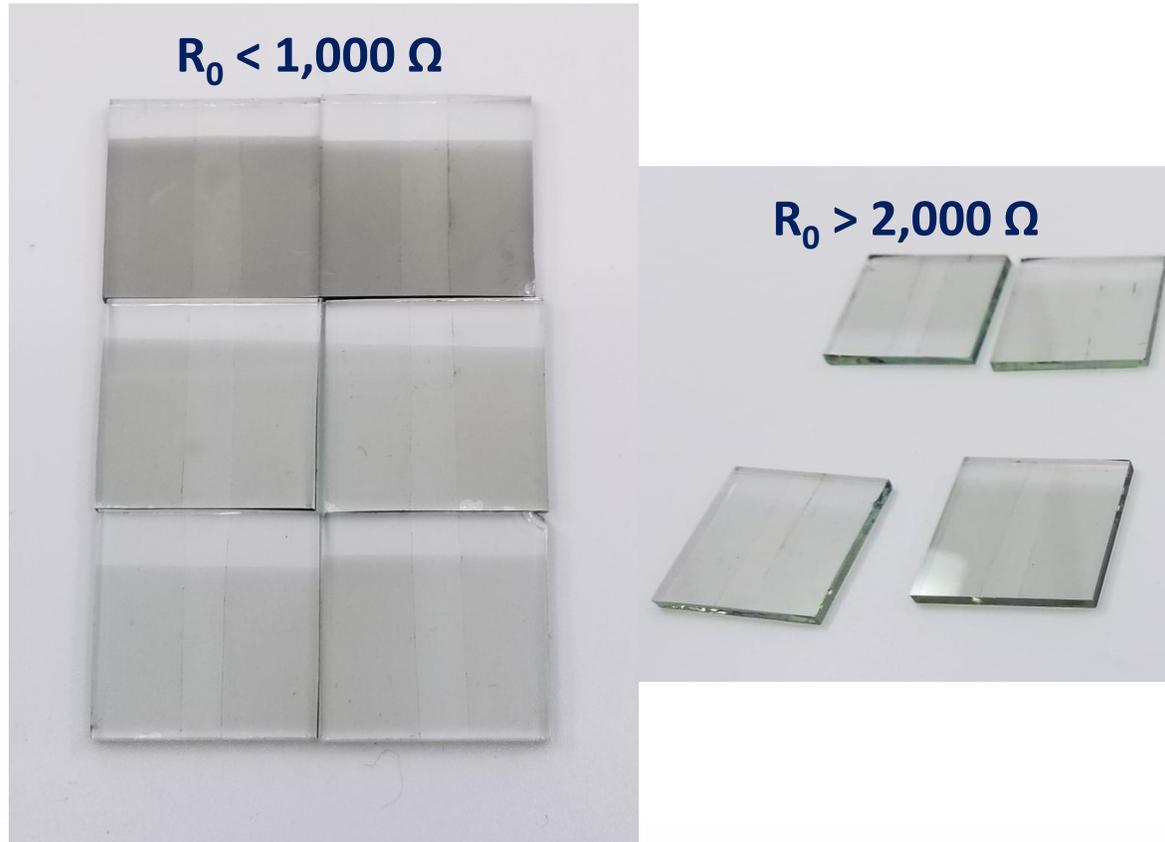


Thanks to Dr. Meiping Zhu for generating figure of Ti₃C₂T_x contact method.

16 μm Free-standing Film of $\text{Mo}_2\text{TiC}_2\text{T}_x$



Spray Coating of $Ti_3C_2T_x$ and $Mo_2TiC_2T_x$



Thickness →

← Initial Resistance

Test Environment with and without Mask

Quartz Window

Containment Unit



Removal and Application of Mask

Sample Electrode

Airtight Seal

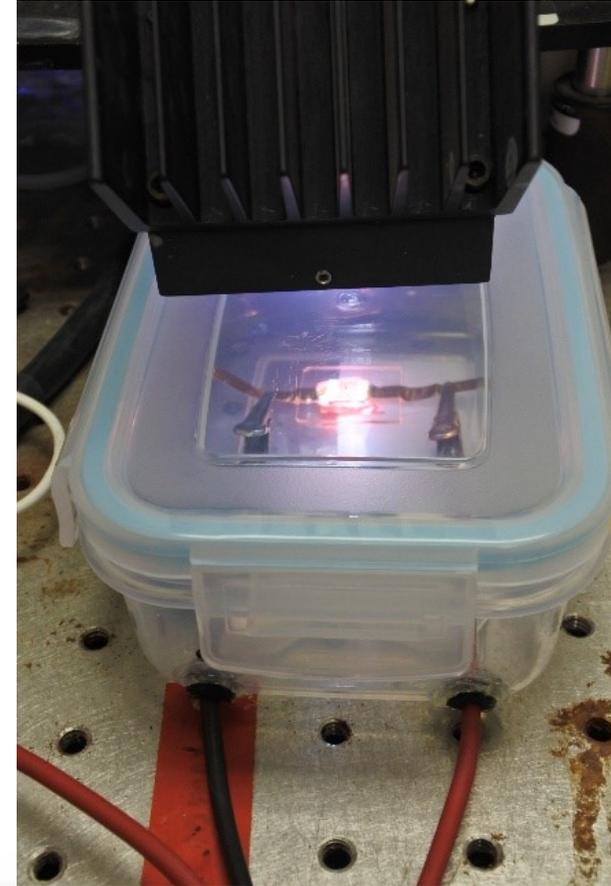


Mask



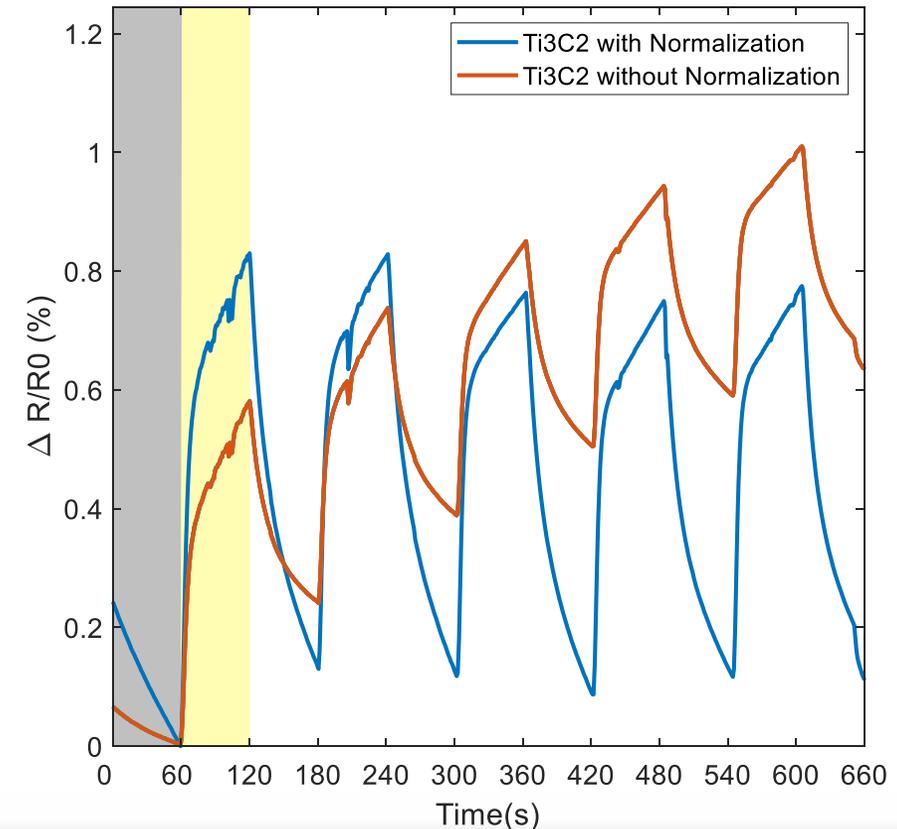
Optoelectronic Characterization

- White light
 - ~350 to 800 nm light
 - 0.85 sun intensity
- Apply constant current
 - Measure voltage
 - Calculate resistance
- Chopped illumination
 - 15 s cycles for pristine glass slides
 - 60 s cycles for FTO



Data Analysis and Manipulation

- Establish baseline using MATLAB
 - Reduces external influences
 - Reduces drift
- Normalize across all cycles
 - ΔR : difference between maxima and minima around change in cycle
 - R_0 : initial resistance averaged for all cycles



Measuring the Photoresponse of $\text{Ti}_3\text{C}_2\text{T}_x$ and $\text{Mo}_2\text{TiC}_2\text{T}_x$

Controlled Variables

- Substrate preparation
- Light intensity
- Spectrum of light
- Inert environment

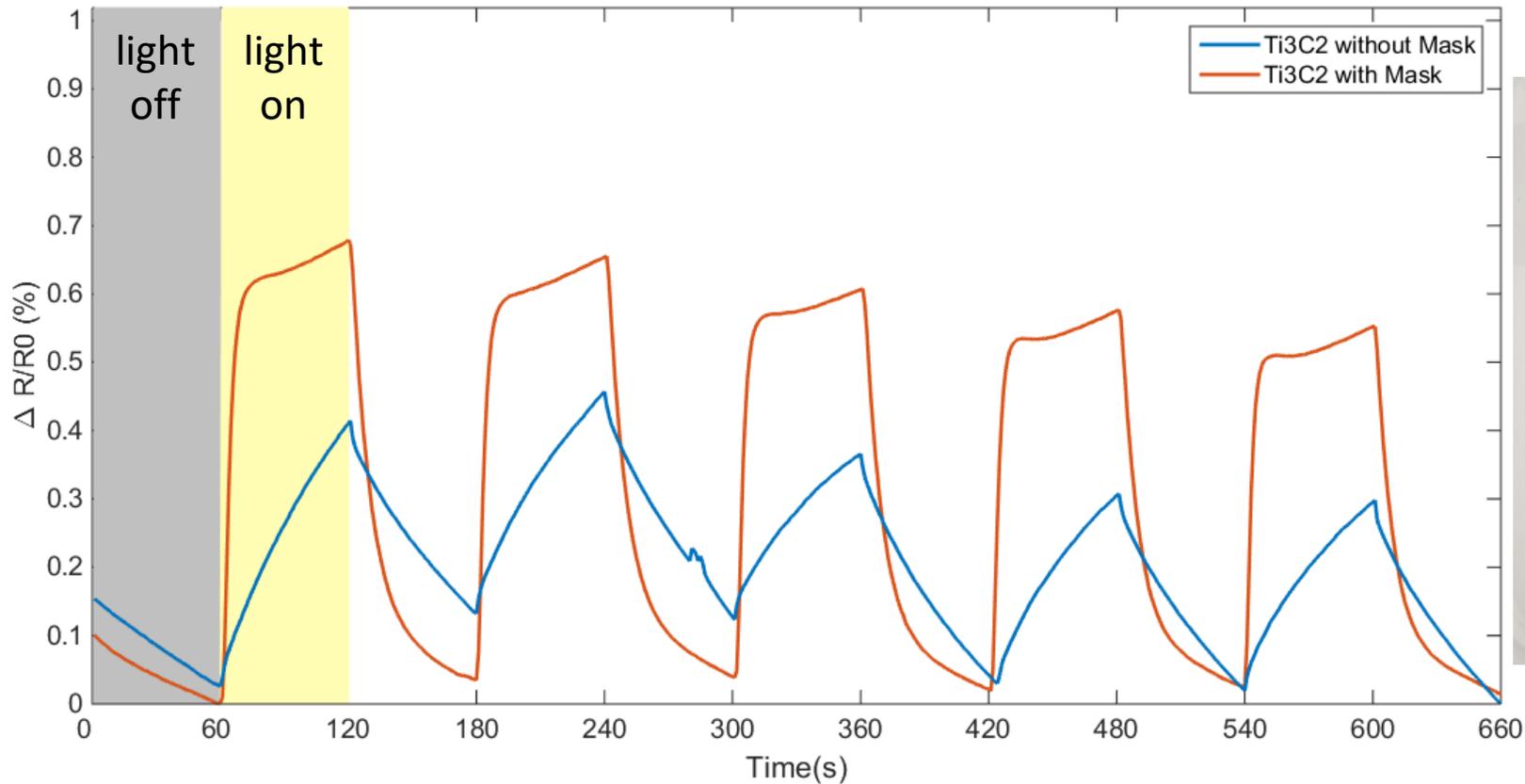
Manipulated Variables

- Contact method
- Film thickness
- Presence of Mask
- Atmosphere

Mask Improves Response of $300 \Omega \text{Ti}_3\text{C}_2\text{T}_x$ with Ag



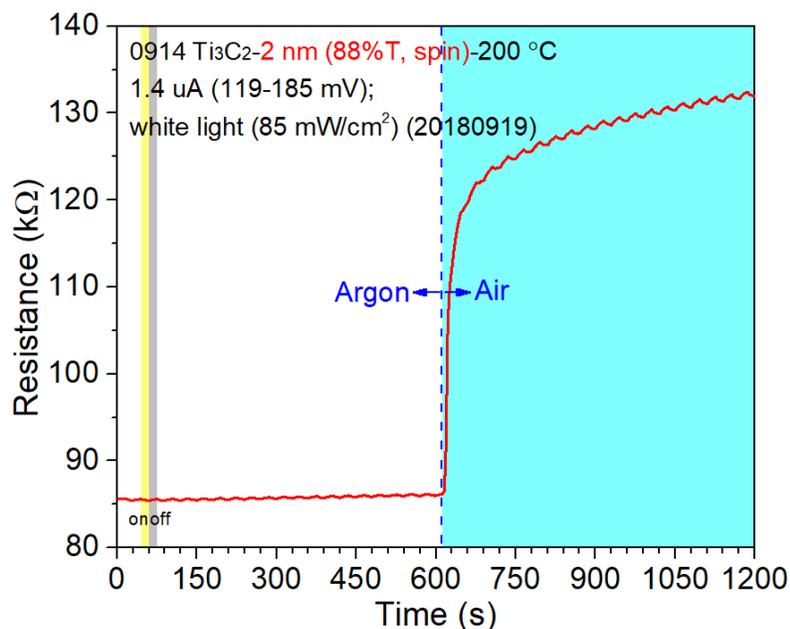
Without Mask



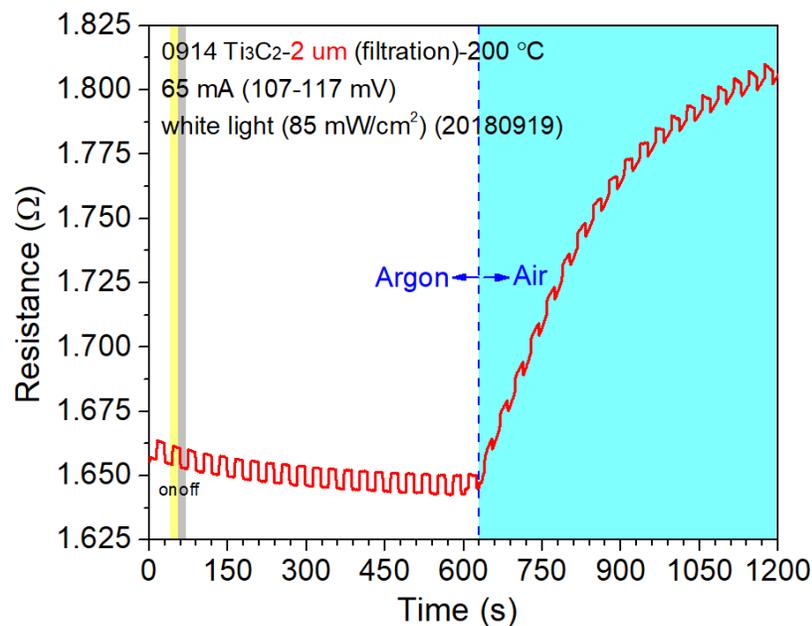
With Mask

Exposure to Air Increases Resistance of $Ti_3C_2T_x$

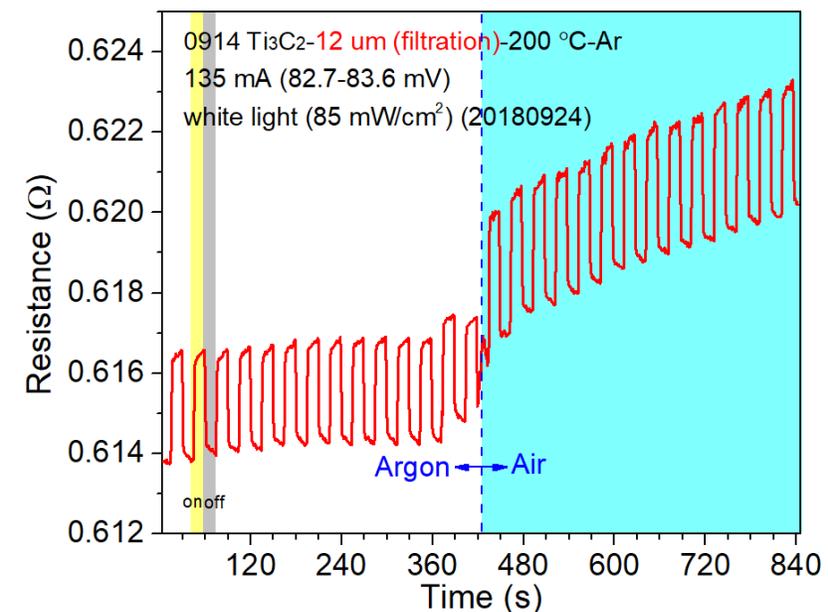
$R_0 \sim 85 \Omega$



$R_0 \sim 1.66 \Omega$

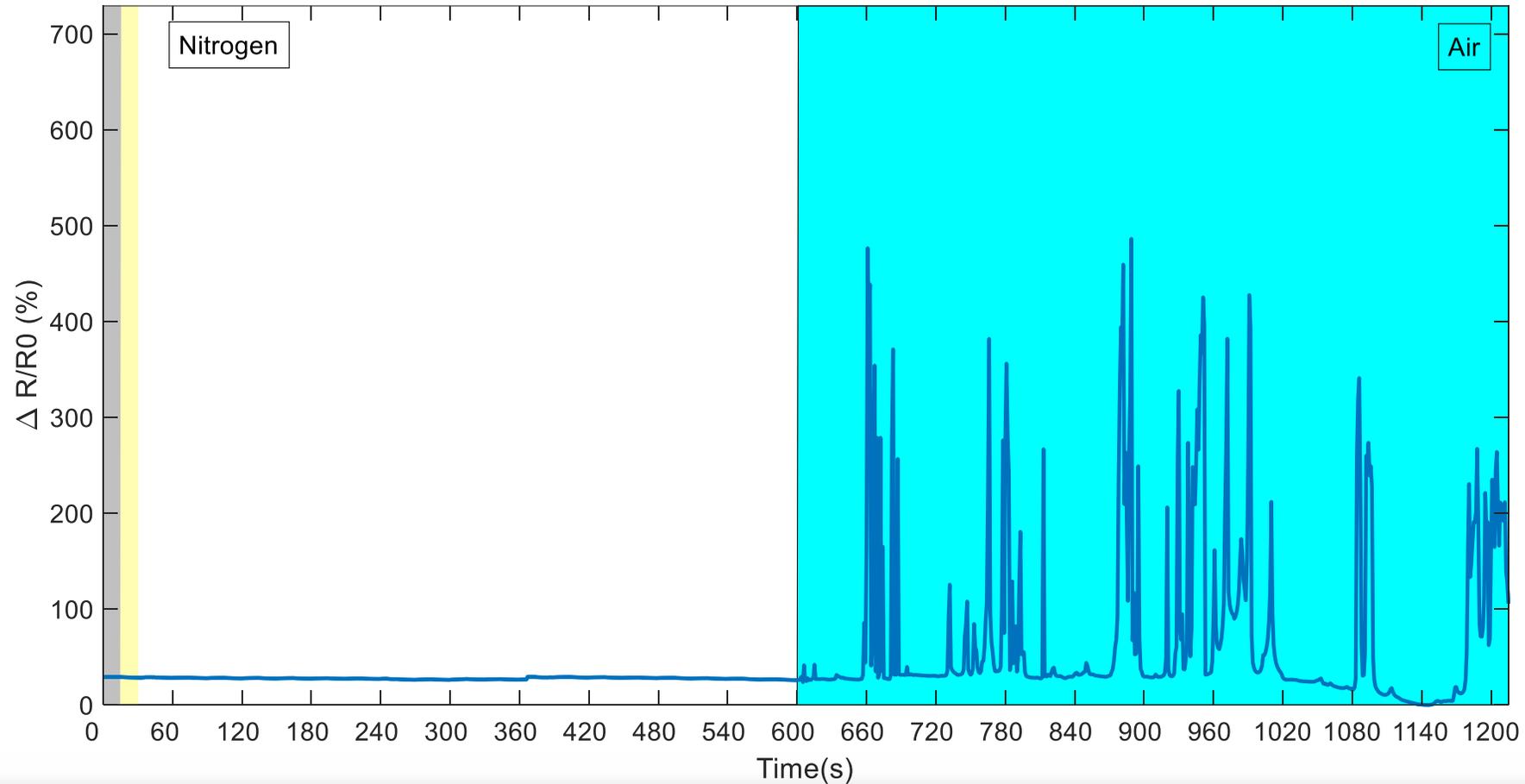


$R_0 \sim 0.614 \Omega$



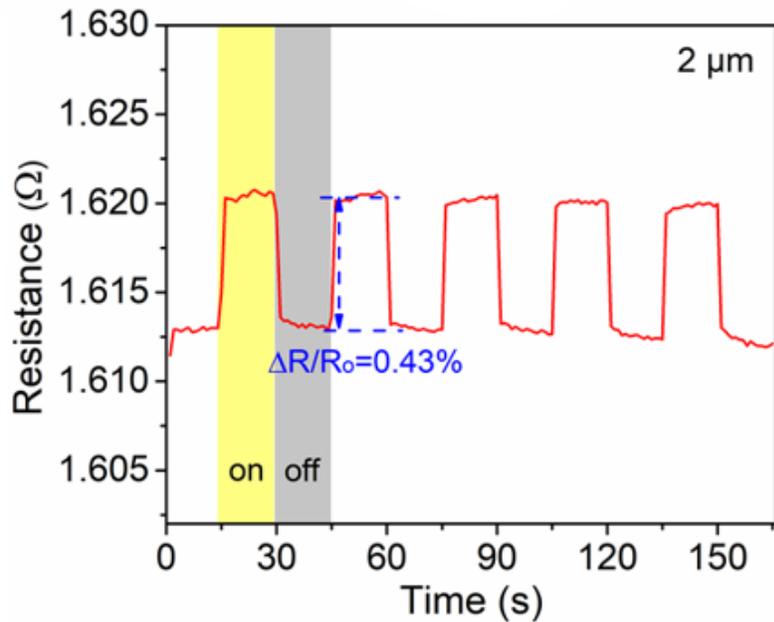
Thanks to Dr. Meiping Zhu for generating figures

Air also Destabilizes $R_0 \sim 3,000 \Omega \text{ Mo}_2\text{TiC}_2\text{T}_x$

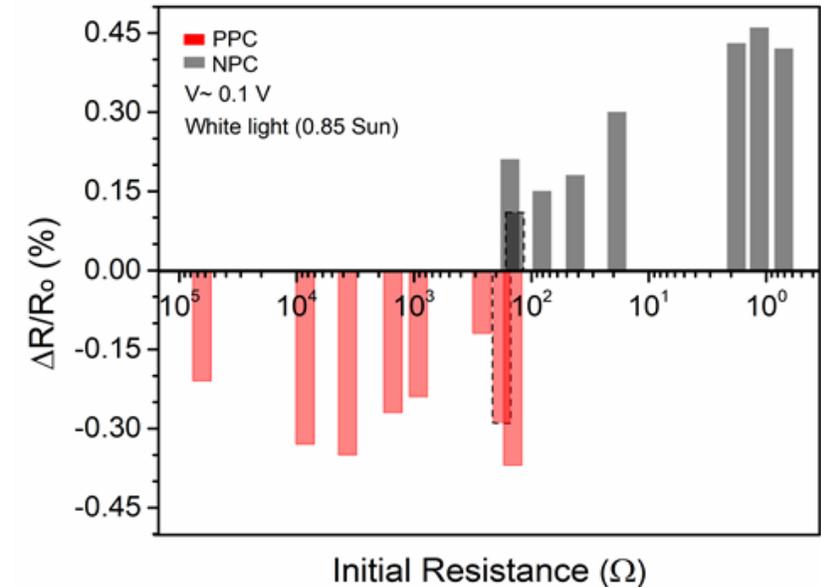
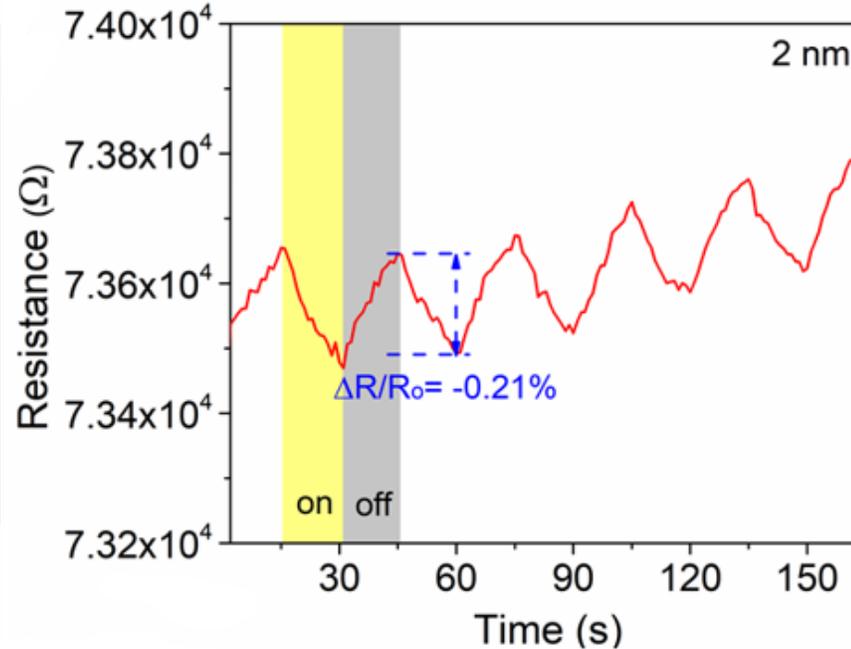


Ti₃C₂T_x on Glass Slides with Ag-Cu Contact Experiences Switch in Photoconductivity

Negative
Photoconductivity



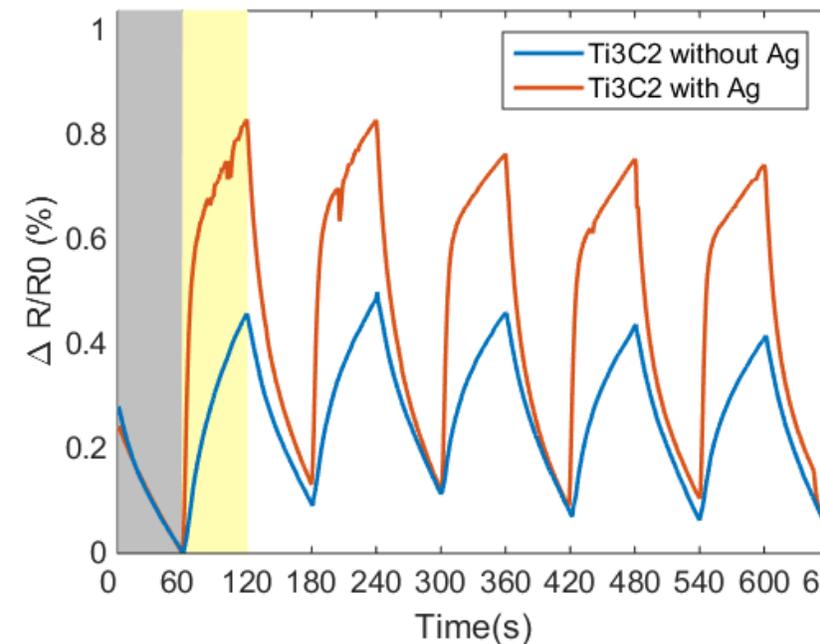
Positive
Photoconductivity



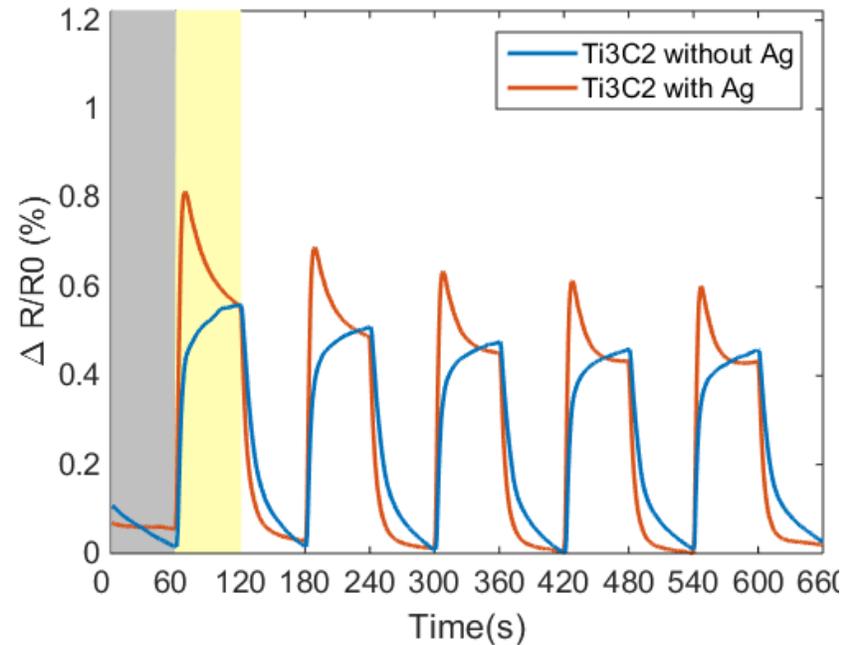
Thanks to Dr. Meiping Zhu for generating figures

Ag-FTO Contact Influence on $Ti_3C_2T_x$ Lacks Consistency

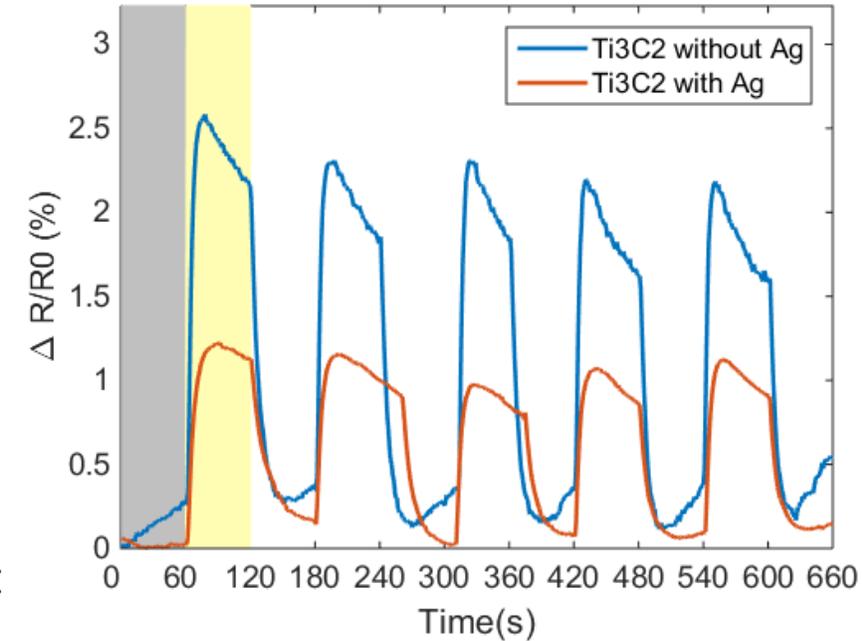
$R_0 \sim 260 - 300 \Omega$



$R_0 \sim 800 - 900 \Omega$

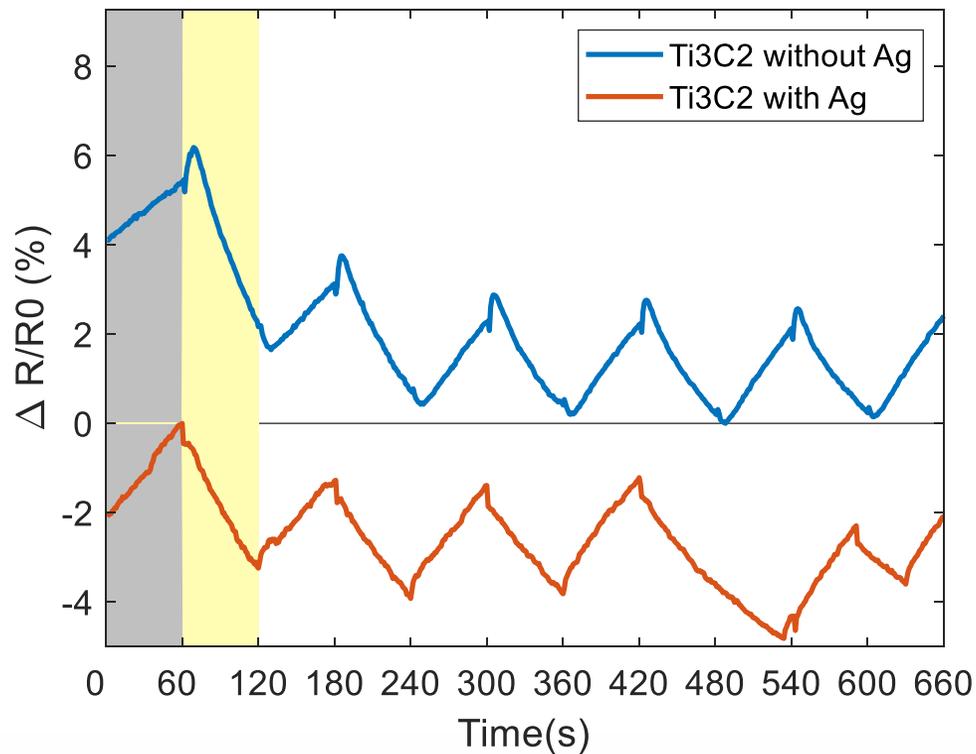


$R_0 \sim 2,000 \Omega$

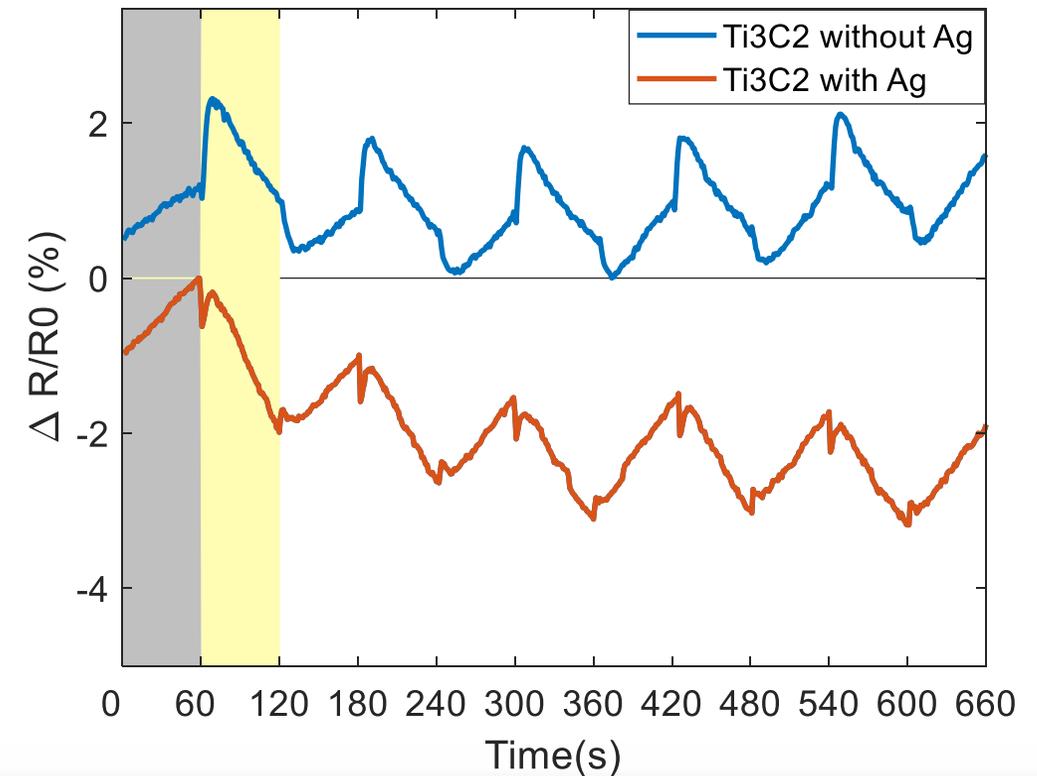


Ag-FTO Contact Switches Photoconductivity of $\text{Ti}_3\text{C}_2\text{T}_x$

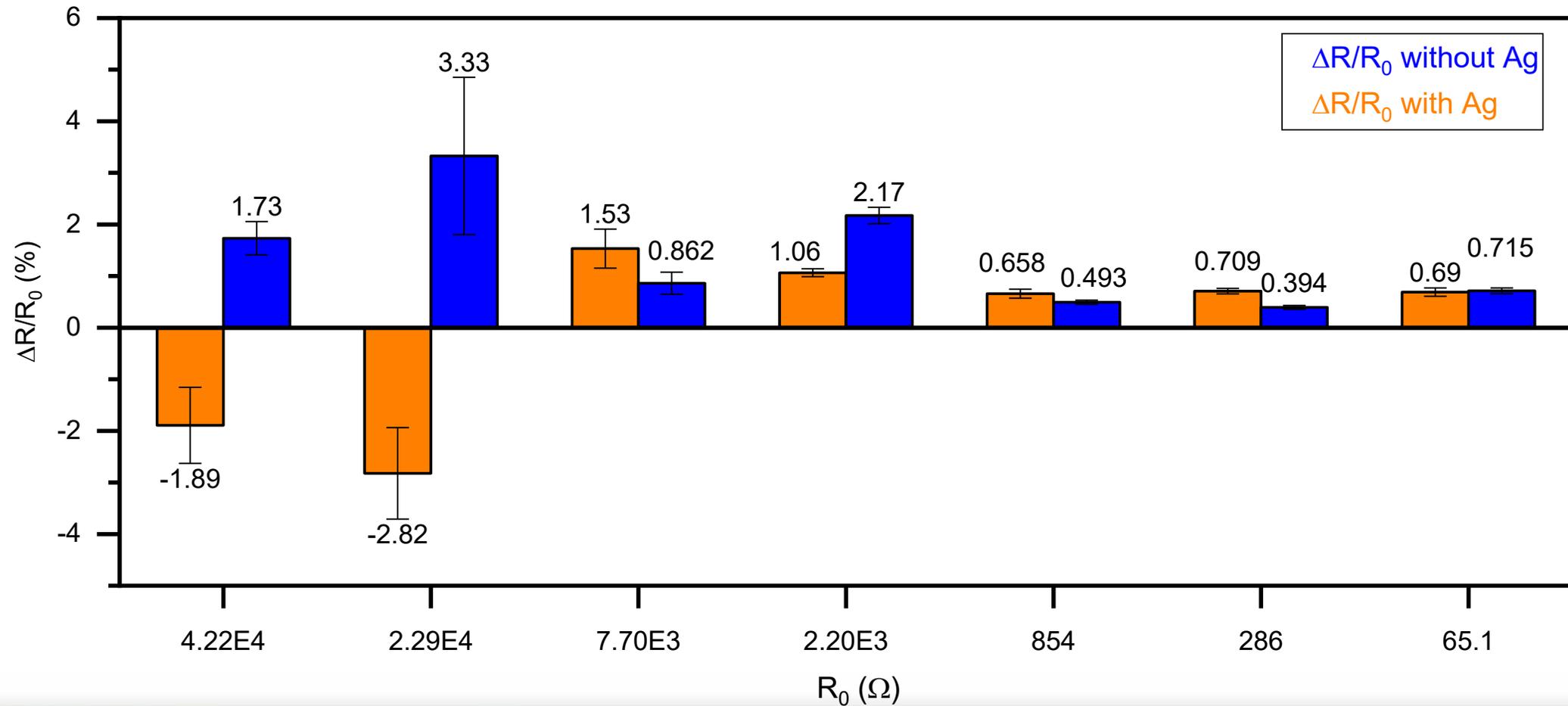
$R_0 \sim 19,000 \Omega$



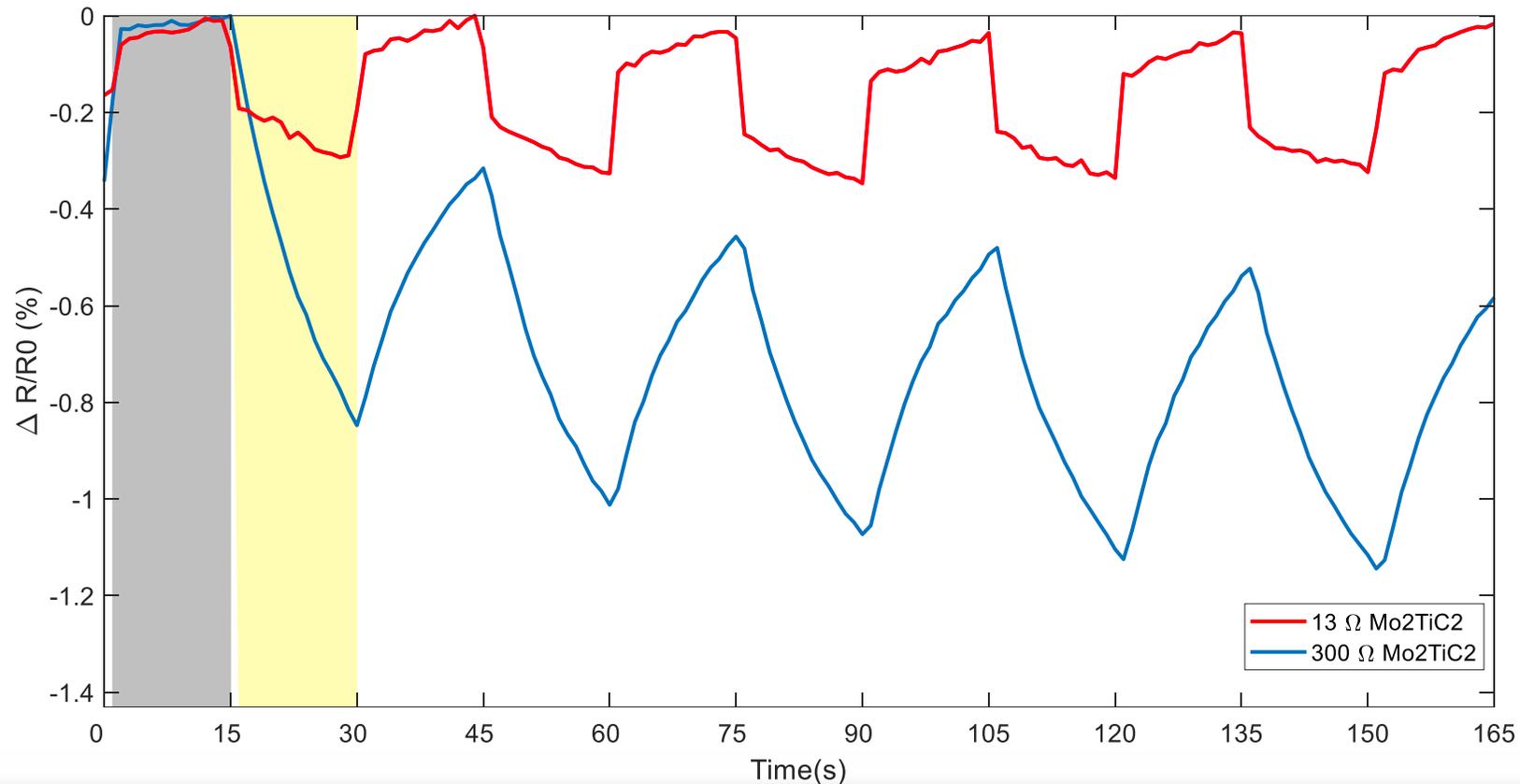
$R_0 \sim 45,000 \Omega$



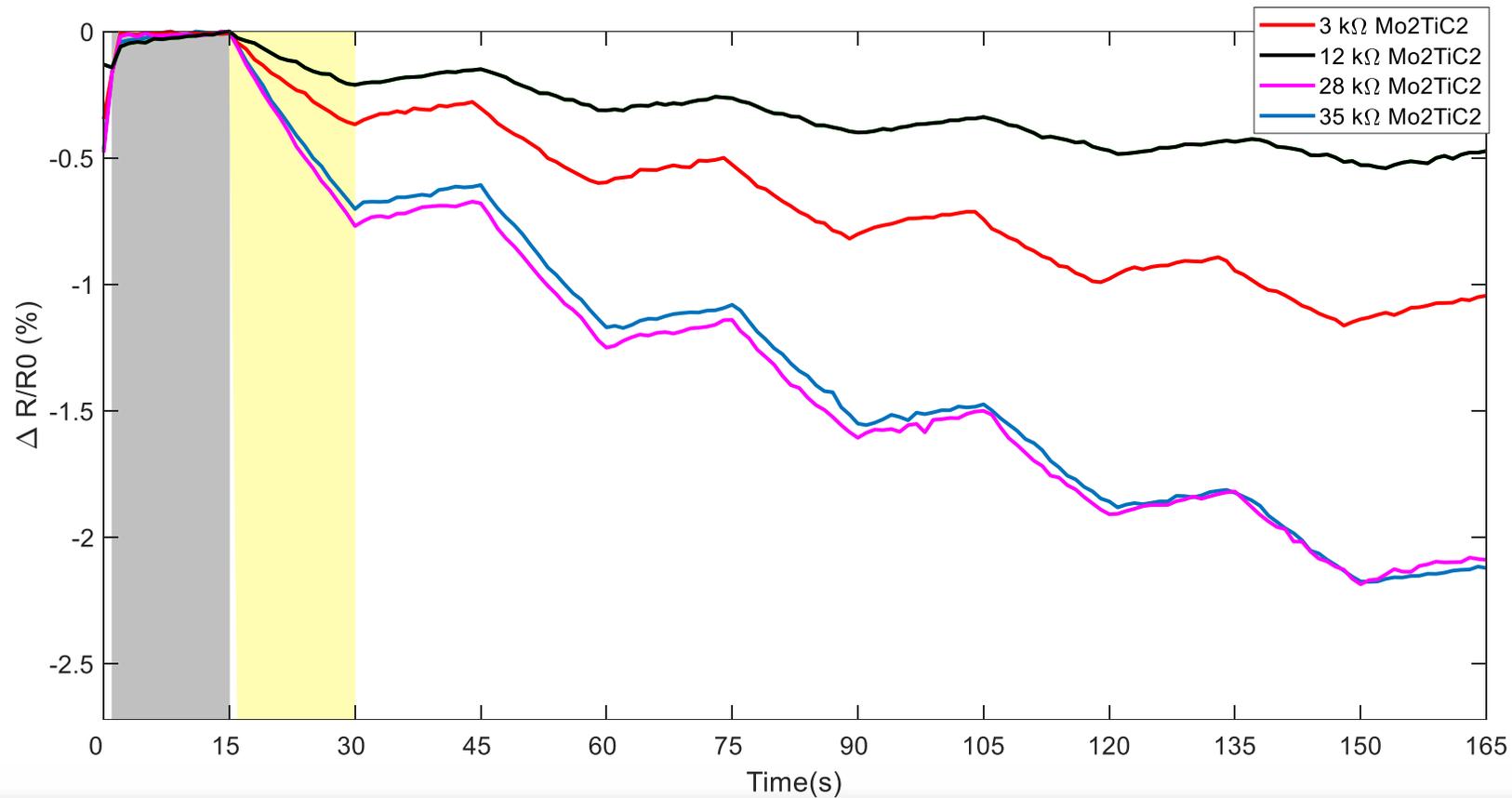
Ti₃C₂T_x Experiences Switch in Photoconductivity upon Ag Contact Application



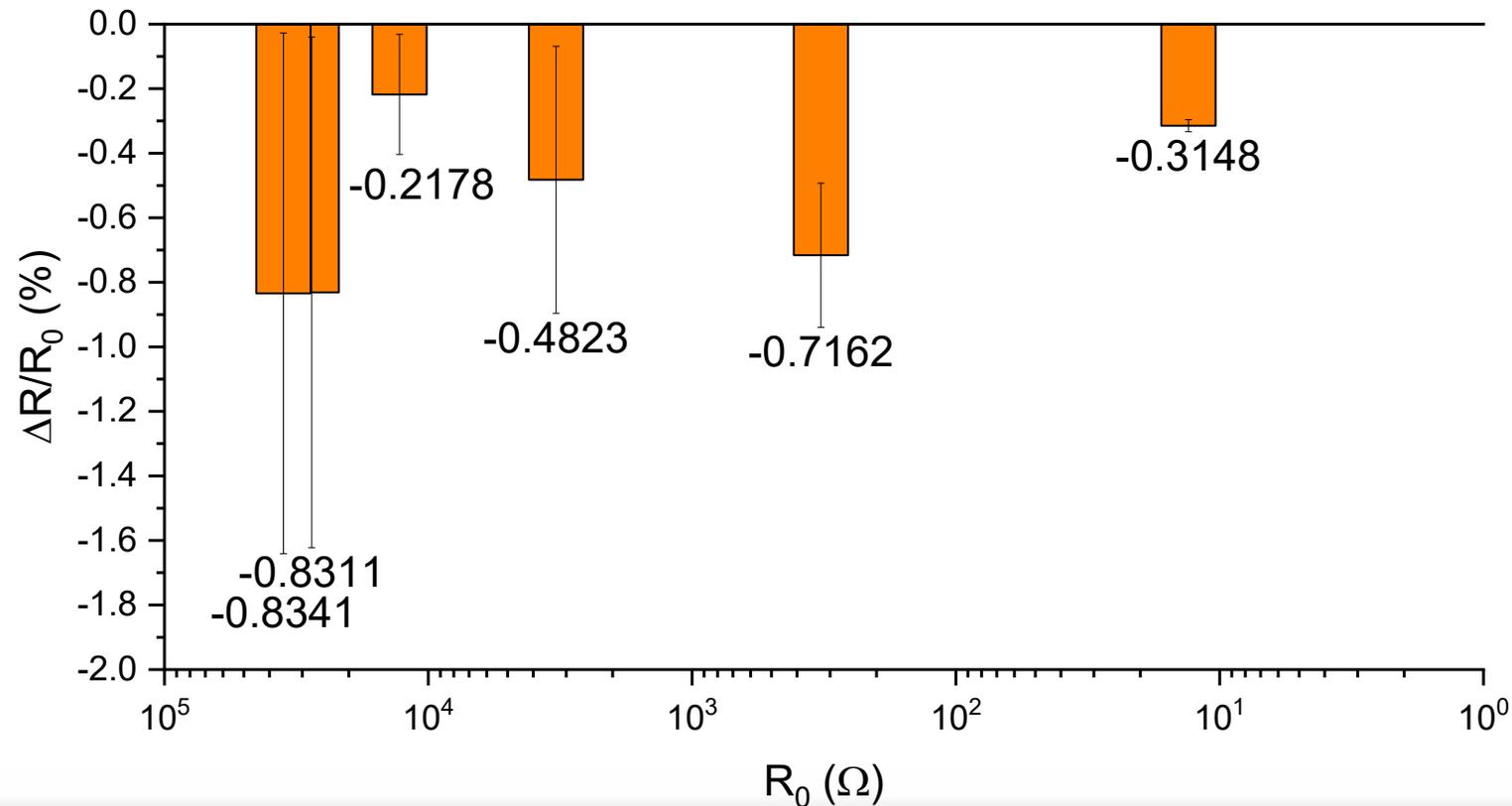
$\text{Mo}_2\text{TiC}_2\text{T}_x$ on Glass Slides with Ag-Cu Contact Exhibits Positive Photoconductivity



Thinner $\text{Mo}_2\text{TiC}_2\text{T}_x$ on Glass Slides Exhibit Gradual Positive Photoconductivity

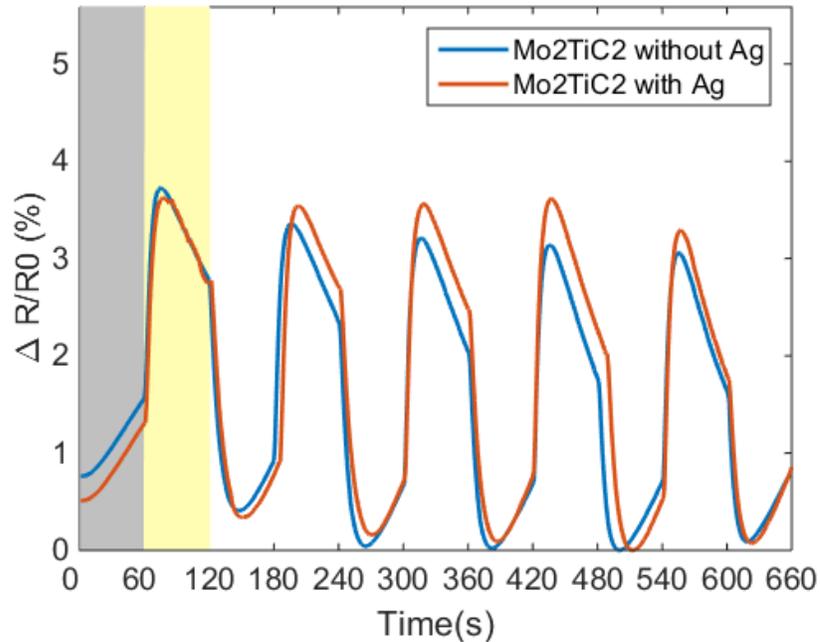


Mo₂TiC₂T_x on Glass Slides Exhibit Consistent Positive Photoconductivity

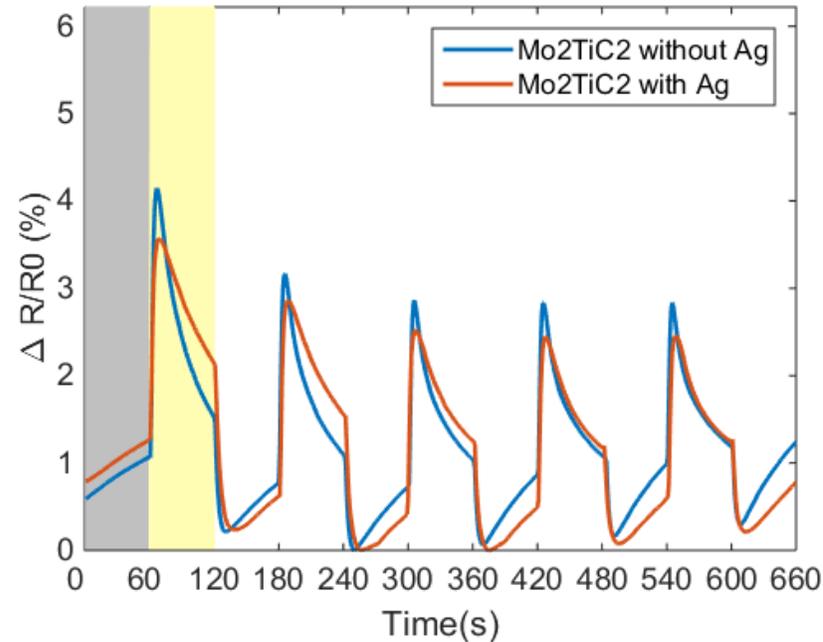


Ag Contact does not Significantly Influence Photoresponse of $\text{Mo}_2\text{TiC}_2\text{T}_x$ on FTO

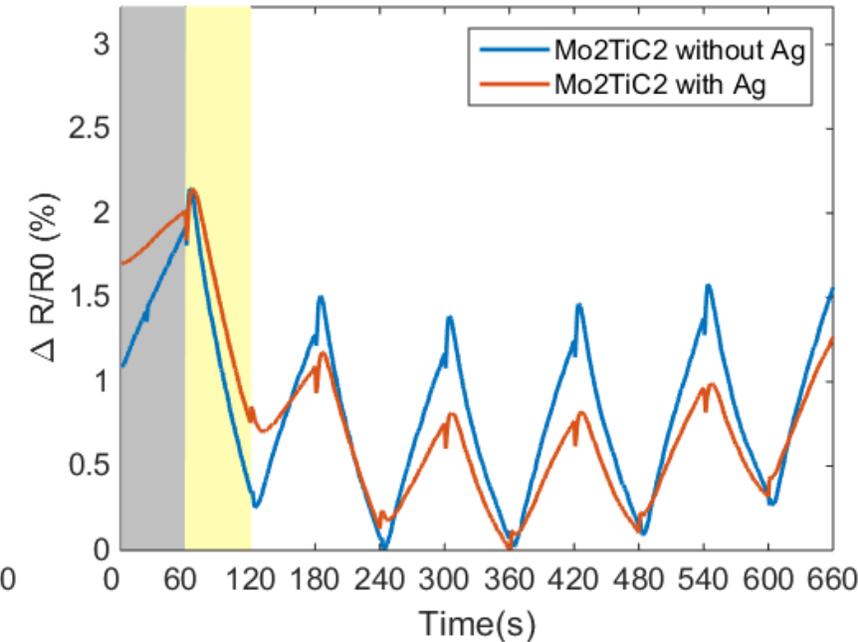
$R_0 \sim 120 \Omega$



$R_0 \sim 450 \Omega$



$R_0 \sim 26,000 \Omega$

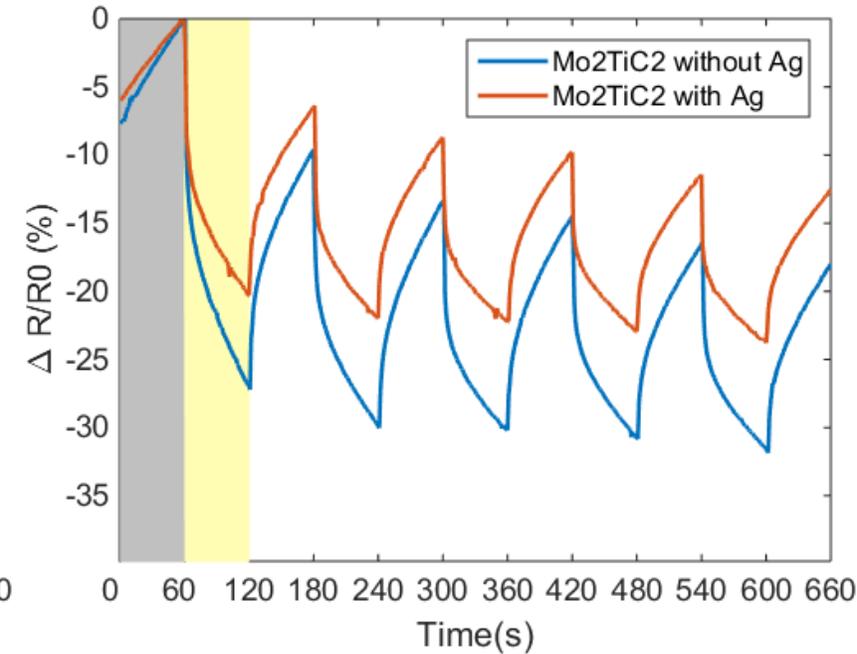
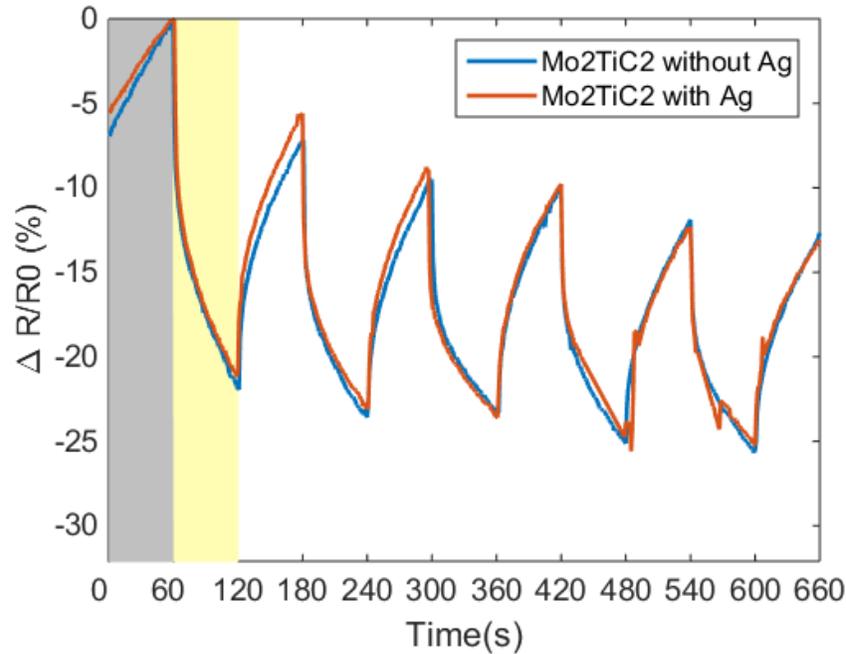
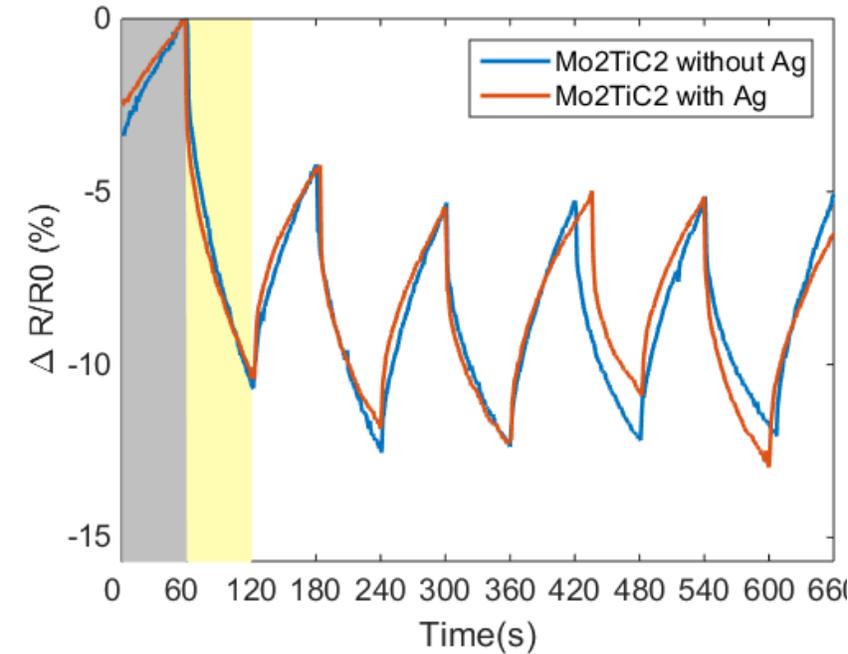


Thin $\text{Mo}_2\text{TiC}_2\text{T}_x$ Films on FTO Exhibit Consistent Positive Photoconductivity

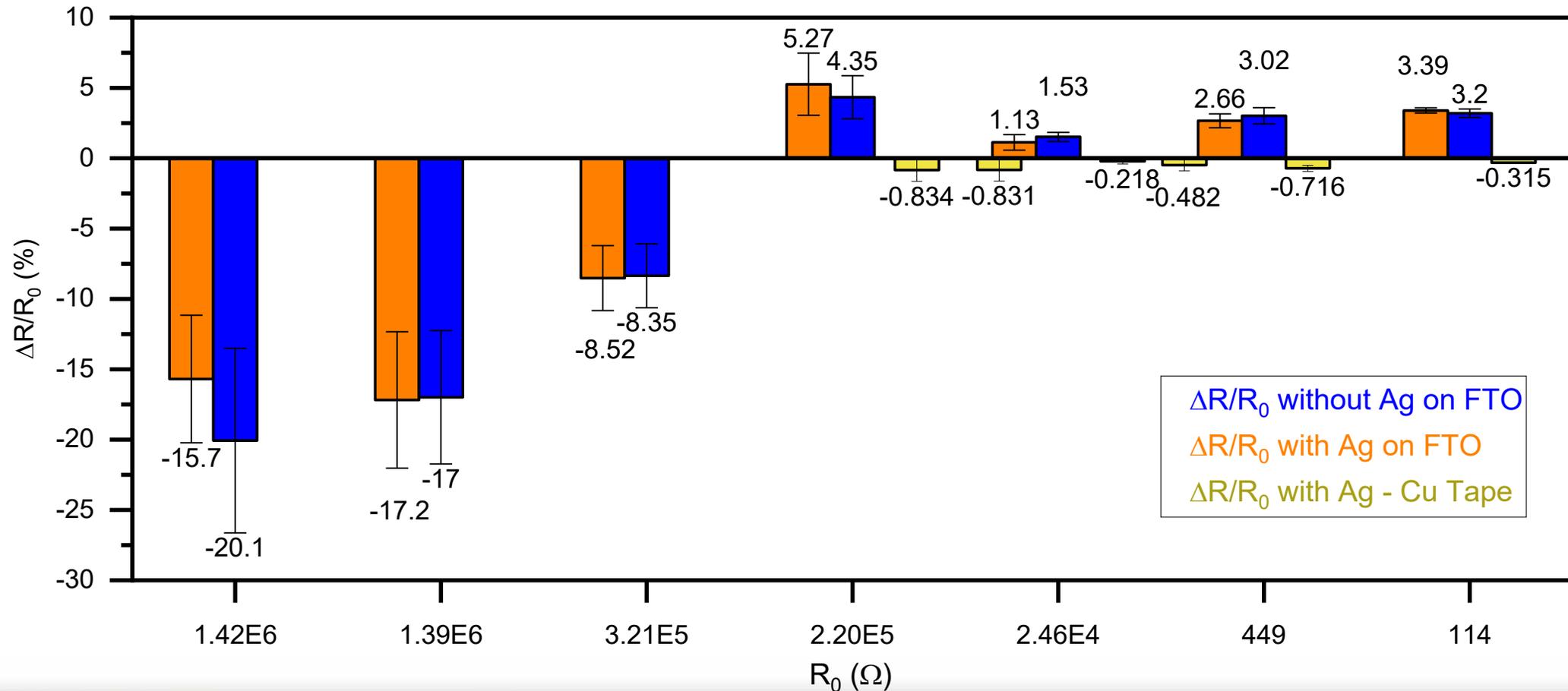
$R_0 \sim 320,000 \Omega$

$R_0 \sim 1,420,000 \Omega$

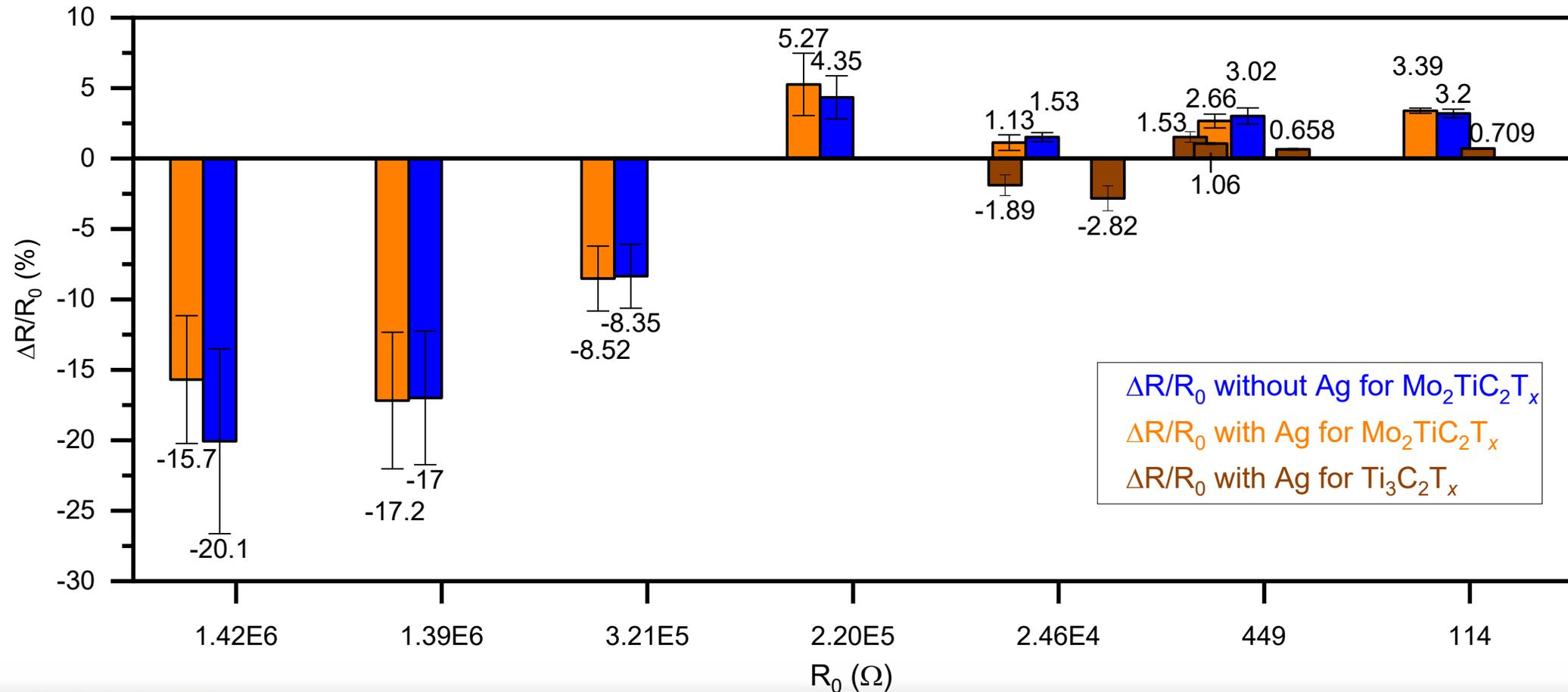
$R_0 \sim 1,450,000 \Omega$



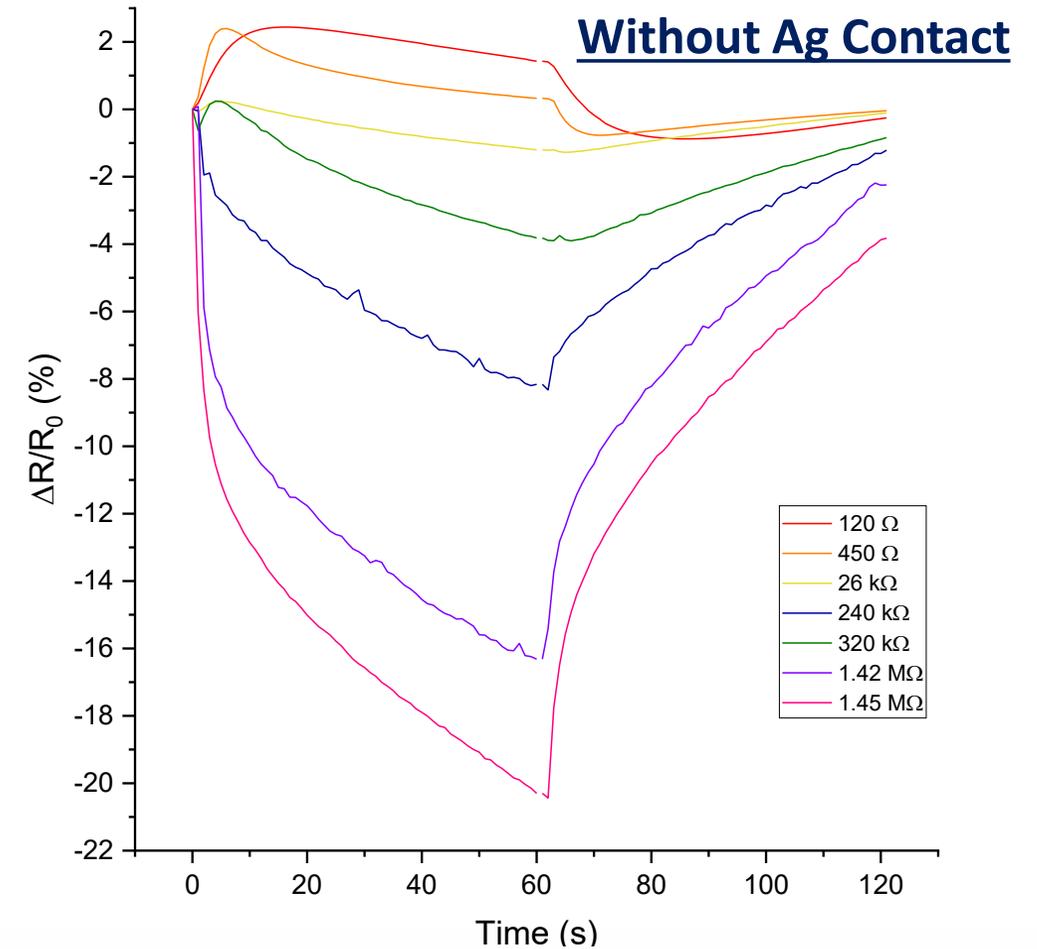
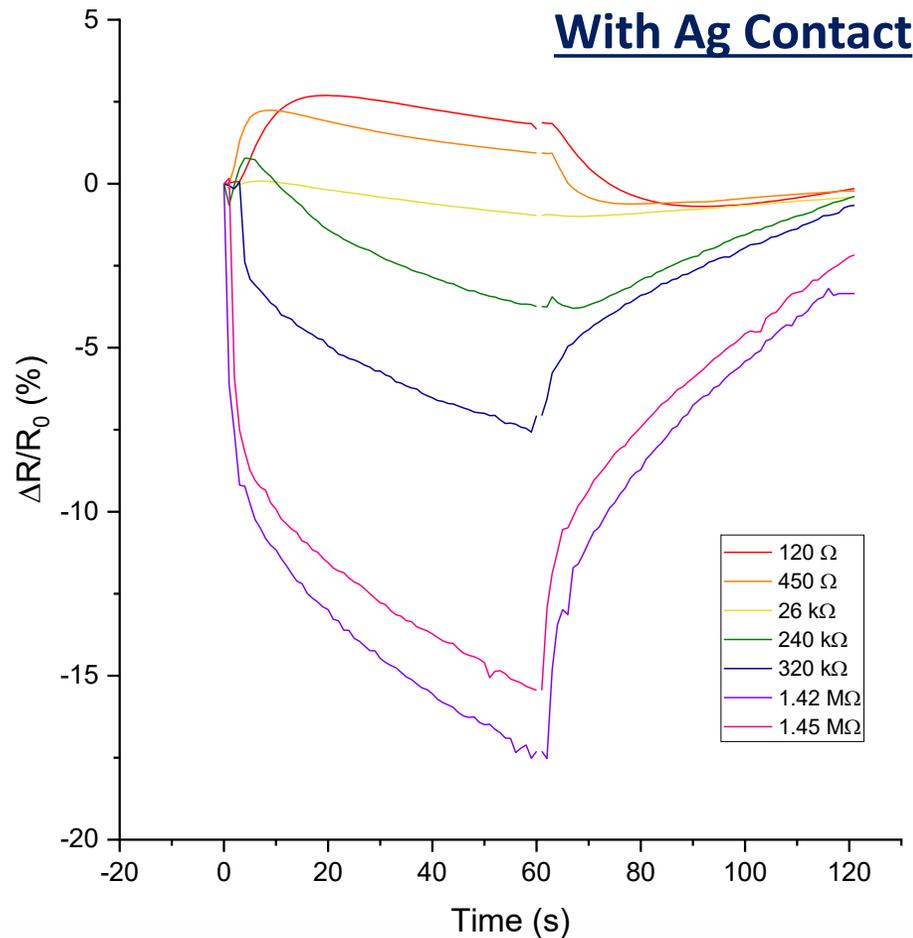
Contact Method Determines Measured Photoconductivity of $\text{Mo}_2\text{TiC}_2\text{T}_x$



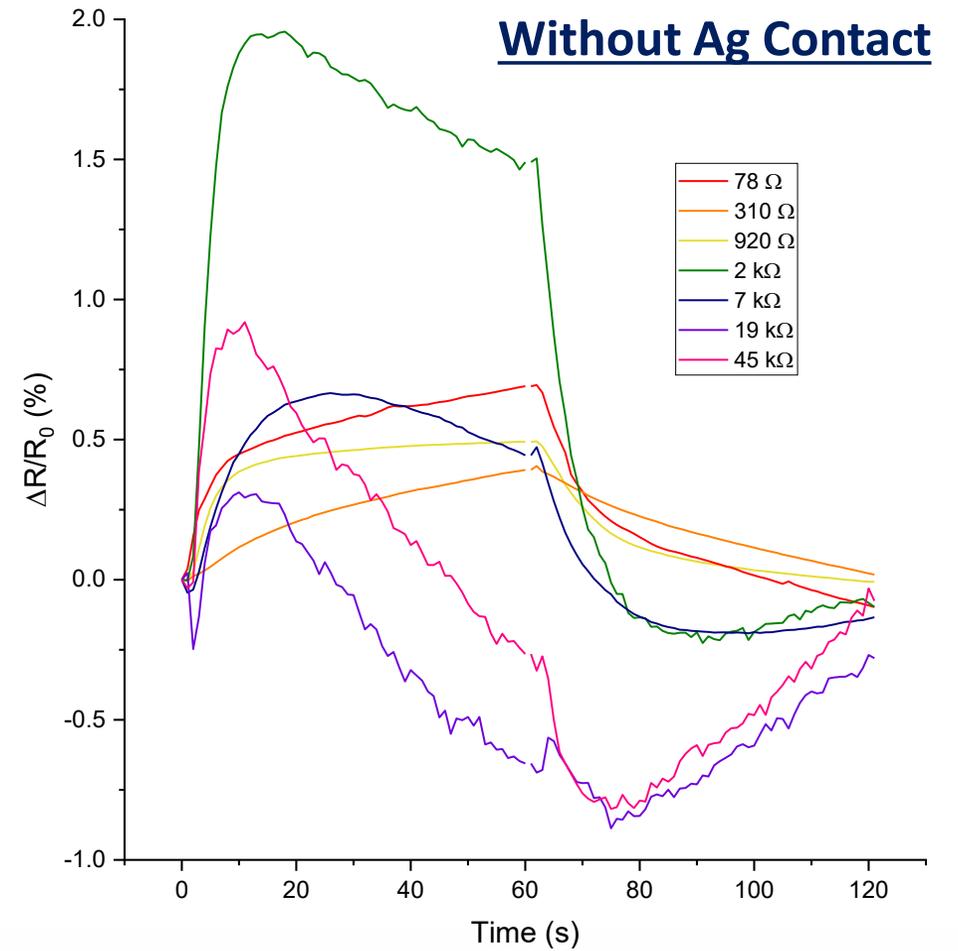
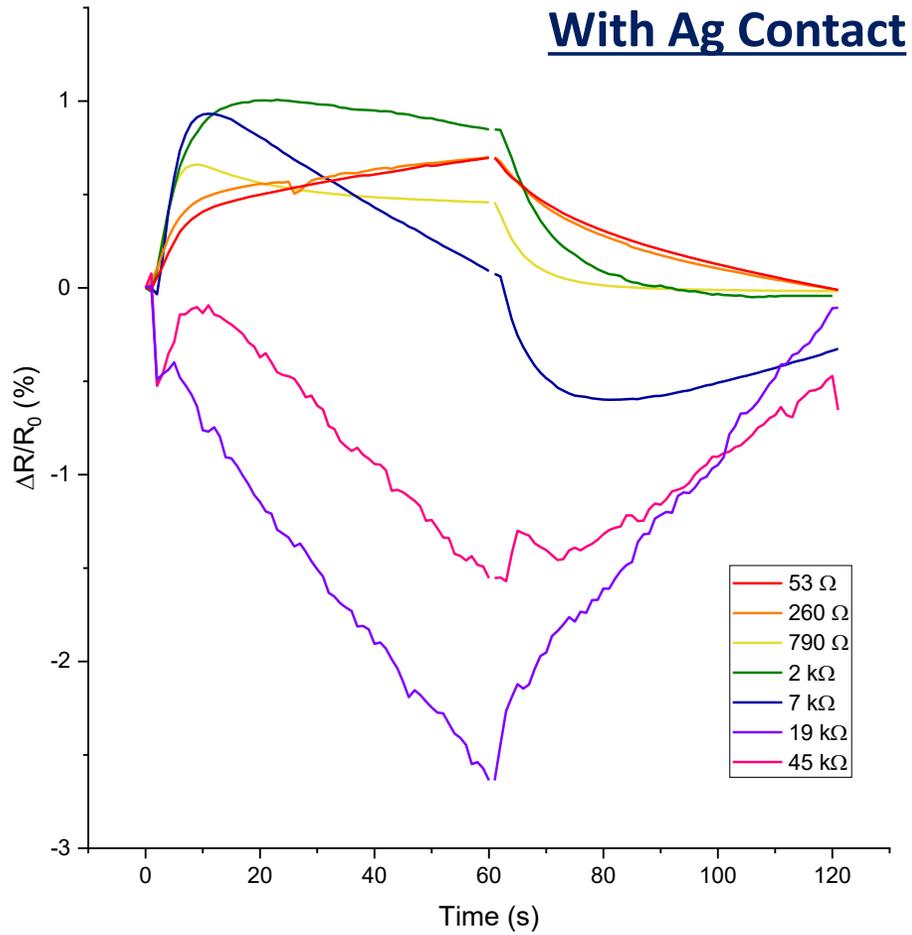
Mo₂TiC₂T_x Experiences Larger Change in Resistance than Ti₃C₂T_x



Mo₂TiC₂T_x Shows Increase in Resistance Change with Decreasing Thickness



Ti₃C₂T_x Photoresponse Lacks Trend with Decreasing Thickness



Conclusions

- Best practices:
 - Mask inactive area during optoelectronic characterization
 - Use patterned FTO or other transparent conducting oxide as contact method
 - Maintain inert environment
- Ti_3C_2 (without Ag contact): negative photoconductivity
- Mo_2TiC_2 : switch from negative to positive photoconductivity

Future Work

- Probe intrinsic optoelectronic behavior of free-standing films
- Measure wavelength-dependent photoresponse of $\text{Mo}_2\text{TiC}_2\text{T}_x$ to verify positive photoconductivity
- Utilize terahertz spectroscopy to disentangle thermal and electronic influences
- Vary substrates to aid in heat transfer

Questions?

Thank you!